

CPC COOPERATIVE PATENT CLASSIFICATION

H ELECTRICITY

(NOTE omitted)

H01 ELECTRIC ELEMENTS

(NOTES omitted)

H01J ELECTRIC DISCHARGE TUBES OR DISCHARGE LAMPS (spark-gaps [H01T](#); arc lamps with consumable electrodes [H05B](#); particle accelerators [H05H](#))

NOTES

1. This subclass covers only devices for producing, influencing, or using a flow of electrons or ions, e.g. for controlling, indicating, or switching of electric current, counting electric pulses, producing light or other electromagnetic oscillations, such as X-rays, or for separating or analysing radiation or particles, and having a closed or substantially closed casing containing a chosen gas, vapour, or vacuum, upon the pressure and nature of which the characteristics of the device depend. Light sources using a combination (other than covered by group [H01J 61/96](#) of this subclass) of discharge and other kinds of light generation are dealt with in [H05B 35/00](#).
2. In this subclass, groups [H01J 1/00](#) - [H01J 7/00](#) relate only to:
 - i. details of an unspecified kind of discharge tube or lamp, or
 - ii. details mentioned in a specification as applicable to two or more kinds of tubes or lamps as defined by groups [H01J 11/00](#), [H01J 13/00](#), [H01J 15/00](#), [H01J 17/00](#), [H01J 21/00](#), [H01J 25/00](#), [H01J 27/00](#), [H01J 31/00](#), [H01J 33/00](#), [H01J 35/00](#), [H01J 37/00](#), [H01J 40/00](#), [H01J 41/00](#), [H01J 47/00](#), [H01J 49/00](#), [H01J 61/00](#), [H01J 63/00](#) or [H01J 65/00](#), hereinafter called basic kinds. A detail only described with reference to, or clearly only applicable to, tubes or lamps of a single basic kind is classified in the detail group appropriate to tubes or lamps of that basic kind, e.g. [H01J 17/04](#).
3. In this subclass, the following term is used with the meaning indicated:
 - "lamp" includes tubes emitting ultraviolet or infrared light.
4. Attention is drawn to the definition of the expression "spark gaps" given in the Note following the title of subclass [H01T](#).
5. Apparatus or processes specially adapted for the manufacture of electric discharge tubes, discharge lamps, or parts thereof are classified in group [H01J 9/00](#).

WARNING

In this subclass non-limiting references (in the sense of paragraph 39 of the Guide to the IPC) may still be displayed in the scheme.

1/00	Details of electrodes, of magnetic control means, of screens, or of the mounting or spacing thereof, common to two or more basic types of discharge tubes or lamps (details of electron-optical arrangements or of ion traps H01J 3/00)	1/144 with other metal oxides as an emissive material
		1/146 with metals or alloys as an emissive material
		1/148 with compounds having metallic conductive properties, e.g. lanthanum boride, as an emissive material
1/02	. Main electrodes	1/15	. . . Cathodes heated directly by an electric current
1/025	. . { Hollow cathodes }	1/16 characterised by the shape
1/04	. . Liquid electrodes, e.g. liquid cathode	1/18 Supports; Vibration-damping arrangements
1/05	. . . characterised by material	1/20	. . . Cathodes heated indirectly by an electric current; Cathodes heated by electron or ion bombardment
1/06	. . . Containers for liquid-pool electrodes; Arrangement or mounting thereof	1/22 Heaters
1/08	. . . Positioning or moving the cathode spot on the surface of a liquid-pool cathode	1/24 Insulating layer or body located between heater and emissive material
1/10	. . . Cooling, heating, circulating, filtering, or controlling level of liquid in a liquid-pool electrode	1/26 Supports for the emissive material
1/12	. . Cathodes having mercury or liquid alkali metal deposited on the cathode surface during operation of the tube	1/28 Dispenser-type cathodes, e.g. L-cathode
1/13	. . Solid thermionic cathodes	1/30	. . Cold cathodes, e.g. field-emissive cathode
1/135	. . . { Circuit arrangements therefor, e.g. for temperature control }	1/304	. . . Field-emissive cathodes
1/14	. . . characterised by the material	1/3042 { microengineered, e.g. Spindt-type }
1/142 with alkaline-earth metal oxides, or such oxides used in conjunction with reducing agents, as an emissive material	1/3044 { Point emitters }
		1/3046 { Edge emitters }
		1/3048 { Distributed particle emitters }
		1/308	. . . Semiconductor cathodes, e.g. cathodes with PN junction layers

- 1/312 . . . having an electric field perpendicular to the surface, e.g. tunnel-effect cathodes of metal-insulator-metal [MIM] type ([H01J 1/304-H01J 1/308 take precedence](#))
 - 1/316 . . . having an electric field parallel to the surface, e.g. thin film cathodes
 - 1/32 . . Secondary-electron-emitting electrodes ([H01J 1/35 takes precedence](#))
 - 1/34 . . Photo-emissive cathodes ([H01J 1/35 takes precedence](#))
 - 1/35 . . Electrodes exhibiting both secondary emission and photo-emission
 - 1/36 . . Solid anodes; Solid auxiliary anodes for maintaining a discharge
 - 1/38 . . . characterised by the material
 - 1/40 . . . forming part of the envelope of the tube or lamp
 - 1/42 . . . Cooling of anodes ([cooling rotary anodes H01J 1/44](#)); Heating of anodes
 - 1/44 . . . Rotary anodes; Arrangements for rotating anodes; Cooling rotary anodes
 - 1/46 . Control electrodes, e.g. grid ([for igniting arrangements H01J 7/30](#)); Auxiliary electrodes ([auxiliary anodes for maintaining a discharge H01J 1/36](#))
 - 1/48 . . characterised by the material
 - 1/50 . Magnetic means for controlling the discharge
 - 1/52 . Screens for shielding; Guides for influencing the discharge; Masks interposed in the electron stream
 - 1/53 . Electrodes intimately associated with a screen on or from which an image or pattern is formed, picked-up, converted, or stored
 - 1/54 . Screens on or from which an image or pattern is formed, picked-up, converted, or stored; Luminescent coatings on vessels
 - 1/56 . . acting as light valves by shutter operation, e.g. for eidophor
 - 1/58 . . acting by discolouration, e.g. halide screen
 - 1/60 . . Incandescent screens
 - 1/62 . . Luminescent screens; Selection of materials for luminescent coatings on vessels
 - 1/63 . . . characterised by the luminescent material
 - 1/64 . . . characterised by the binder or adhesive for securing the luminescent material to its support
 - 1/66 . . . Supports for luminescent material
 - 1/68 . . . with superimposed luminescent layers
 - 1/70 . . . with protective, conductive, or reflective layers
 - 1/72 . . . with luminescent material discontinuously arranged, e.g. in dots or lines
 - 1/74 with adjacent dots or lines of different luminescent material
 - 1/76 . . . provided with permanent marks or references
 - 1/78 . . Photoelectric screens; Charge-storage screens
 - 1/88 . Mounting, supporting, spacing, or insulating of electrodes or of electrode assemblies
 - 1/90 . . Insulation between electrodes or supports within the vacuum space
 - 1/92 . . Mountings for the electrode assembly as a whole
 - 1/94 . . Mountings for individual electrodes
 - 1/96 . . Spacing members extending to the envelope
 - 1/98 . . . without fixed connection between spacing member and envelope
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- 3/00 Details of electron-optical or ion-optical arrangements or of ion traps common to two or more basic types of discharge tubes or lamps**
 - 3/02 . Electron guns
 - 3/021 . . {Electron guns using a field emission, photo emission, or secondary emission electron source}
 - 3/022 . . . {with microengineered cathode, e.g. Spindt-type}
 - 3/023 . . {Electron guns using electron multiplication}
 - 3/024 . . {Electron guns using thermionic emission of cathode heated by electron or ion bombardment or by irradiation by other energetic beams, e.g. by laser}
 - 3/025 . . {Electron guns using a discharge in a gas or a vapour as electron source ([gas-filled discharge tubes with gaseous cathodes H01J 15/00](#))}
 - 3/026 . . {Eliminating deleterious effects due to thermal effects, electric or magnetic field ([H01J 3/021 - H01J 3/025 take precedence](#))}
 - 3/027 . . {Construction of the gun or parts thereof ([H01J 3/021 - H01J 3/025, H01J 3/026 and H01J 3/028 take precedence](#))}
 - 3/028 . . {Replacing parts of the gun; Relative adjustment ([H01J 3/021 - H01J 3/025 take precedence](#))}
 - 3/029 . . {Schematic arrangements for beam forming}
 - 3/04 . Ion guns
 - 3/06 . two or more guns being arranged in a single vacuum space, e.g. for plural-ray tubes ([H01J 3/07 takes precedence](#))
 - 3/07 . Arrangements for controlling convergence of a plurality of beams
 - 3/08 . Arrangements for controlling intensity of ray or beam ([H01J 3/02, H01J 3/04 take precedence](#))
 - 3/10 . Arrangements for centring ray or beam ([H01J 3/02, H01J 3/04 take precedence](#))
 - 3/12 . Arrangements for controlling cross-section of ray or beam; Arrangements for correcting aberration of beam, e.g. due to lenses ([H01J 3/02, H01J 3/04 take precedence](#))
 - 3/14 . Arrangements for focusing or reflecting ray or beam ([H01J 3/02, H01J 3/04 take precedence](#))
 - 3/16 . . Mirrors
 - 3/18 . . Electrostatic lenses
 - 3/20 . . Magnetic lenses
 - 3/22 . . . using electromagnetic means only
 - 3/24 . . . using permanent magnets only
 - 3/26 . Arrangements for deflecting ray or beam
 - 3/28 . . along one straight line or along two perpendicular straight lines
 - 3/30 . . . by electric fields only
 - 3/32 . . . by magnetic fields only
 - 3/34 . . along a circle, spiral, or rotating radial line
 - 3/36 . Arrangements for controlling the ray or beam after passing the main deflection system, e.g. for post-acceleration or post-concentration
 - 3/38 . Mounting, supporting, spacing, or insulating electron-optical or ion-optical arrangements
 - 3/40 . Traps for removing or diverting unwanted particles, e.g. negative ions, fringing electrons; Arrangements for velocity or mass selection ([\(see provisionally also H01J 29/46 - H01J 29/84\)](#))

5/00	Details relating to vessels or to leading-in conductors common to two or more basic types of discharge tubes or lamps	7/06	. . having helium, argon, neon, krypton, or xenon as the principal constituent
5/02	. Vessels; Containers; Shields associated therewith; Vacuum locks	7/08	. . having a metallic vapour as the principal constituent
5/03	. . Arrangements for preventing or mitigating effects of implosion of vessels or containers	7/10	. . . mercury vapour
5/04	. . Vessels or containers characterised by the material thereof	7/12	. . . vapour of an alkali metal
5/06	. . Vessels or containers specially adapted for operation at high tension, e.g. by improved potential distribution over surface of vessel	7/14	. Means for obtaining or maintaining the desired pressure within the vessel
5/08	. . provided with coatings on the walls thereof; Selection of materials for the coatings (luminescent coatings H01J 1/62)	7/16	. . Means for permitting pumping during operation of the tube or lamp
5/10	. . . on internal surfaces	7/18	. . Means for absorbing or adsorbing gas, e.g. by gettering
5/12	. . Double-wall vessels or containers	7/183	. . . {Composition or manufacture of getters}
5/125	. . . {with a gas tight space between both walls}	7/186	. . . {Getter supports}
5/14	. . Dismountable vessels or containers, e.g. for replacing cathode heater	7/20	. . Means for producing, introducing, or replenishing gas or vapour during operation of the tube or lamp
5/16	. . Optical or photographic arrangements structurally combined with the vessel	7/22	. . Tubulations therefor, e.g. for exhausting; Closures therefor
5/18	. . Windows permeable to X-rays, gamma-rays, or particles	7/24	. Cooling arrangements; Heating arrangements; Means for circulating gas or vapour within the discharge space
5/20	. Seals between parts of vessels	7/26	. . by flow of fluid through passages associated with tube or lamp
5/22	. . Vacuum-tight joints between parts of vessel	7/28	. . by latent heat or evaporation of cooling liquid
5/24	. . . between insulating parts of vessel	7/30	. Igniting arrangements
5/26	. . . between insulating and conductive parts of vessel	7/32	. . having resistive or capacitive igniter
5/28	. . . between conductive parts of vessel	7/34	. . . having resistive igniter only
5/30	. . . using packing-material, e.g. sealing-liquid or elastic insert	7/36	. . Igniting by movement of a solid electrode
5/32	. Seals for leading-in conductors	7/38	. . Igniting by movement of vessel as a whole, e.g. tilting
5/34	. . for an individual conductor (pinched-stem seals H01J 5/38 ; end-disc seals H01J 5/40 ; annular seals H01J 5/44)	7/40	. . Igniting by associated radioactive materials or fillings
5/36	. . . using intermediate part	7/42	. Means structurally associated with the tube or lamp for indicating defects or previous use
5/38	. . Pinched-stem or analogous seals	7/44	. One or more circuit elements structurally associated with the tube or lamp
5/40	. . End-disc seals, e.g. flat header	7/46	. . Structurally associated resonator having distributed inductance and capacitance
5/42	. . . using intermediate part	9/00	Apparatus or processes specially adapted for the manufacture {, installation, removal, maintenance} of electric discharge tubes, discharge lamps, or parts thereof; Recovery of material from discharge tubes or lamps
5/44	. . Annular seals disposed between the ends of the vessel	9/003	. {Auxiliary devices for installing or removing discharge tubes or lamps}
5/46	. Leading-in conductors	9/006	. . {for fluorescent lamps}
5/48	. Means forming part of the tube or lamp for the purpose of supporting it	9/02	. Manufacture of electrodes or electrode systems
5/50	. Means forming part of the tube or lamps for the purpose of providing electrical connection to it	9/022	. . {of cold cathodes}
5/52	. . directly applied to or forming part of the vessel	9/025	. . . {of field emission cathodes}
5/54	. . supported by a separate part, e.g. base	9/027	. . . {of thin film cathodes}
5/56	. . . Shape of the separate part	9/04	. . of thermionic cathodes
5/565 {Bases for circular lamps}	9/042	. . . {Manufacture, activation of the emissive part}
5/58	. . . Means for fastening the separate part to the vessel, e.g. by cement	9/045 {Activation of assembled cathode}
5/60 for fastening by mechanical means	9/047 {Cathodes having impregnated bodies (H01J 9/045 takes precedence)}
5/62	. . . Connection of wires protruding from the vessel to connectors carried by the separate part	9/06	. . . Machines therefor
7/00	Details not provided for in the preceding groups and common to two or more basic types of discharge tubes or lamps	9/08	. . Manufacture of heaters for indirectly-heated cathodes
7/02	. Selection of substances for gas fillings; Specified operating pressure or temperature	9/10	. . . Machines therefor
7/04	. . having one or more carbon compounds as the principal constituent	9/12	. . of photo-emissive cathodes; of secondary-emission electrodes
		9/125	. . . {of secondary emission electrodes}

- 9/14 . . of non-emitting electrodes
 - 9/142 . . . {of shadow-masks for colour television tubes}
 - 9/144 {Mask treatment related to the process of dot deposition during manufacture of luminescent screen}
 - 9/146 {Surface treatment, e.g. blackening, coating ([H01J 9/144](#) takes precedence)}
 - 9/148 . . . {of electron emission flat panels, e.g. gate electrodes, focusing electrodes or anode electrodes}
 - 9/16 . . . Machines for making wire grids
 - 9/18 . . Assembling together the component parts of electrode systems
 - 9/185 . . . {of flat panel display devices, e.g. by using spacers}
 - 9/20 . Manufacture of screens on or from which an image or pattern is formed, picked up, converted or stored; Applying coatings to the vessel
 - 9/205 . . {Applying optical coatings or shielding coatings to the vessel of flat panel displays, e.g. applying filter layers, electromagnetic interference shielding layers, anti-reflection coatings or anti-glare coatings}
 - 9/22 . . Applying luminescent coatings
 - 9/221 . . . {in continuous layers}
 - 9/222 {constituted by coated granules emitting light of different colour}
 - 9/223 {by uniformly dispersing of liquid}
 - 9/224 {by precipitation}
 - 9/225 {by electrostatic or electrophoretic processes}
 - 9/227 . . . with luminescent material discontinuously arranged, e.g. in dots or lines
 - 9/2271 {by photographic processes (final treatment of shadow-mask prior to or after dot deposition [H01J 9/144](#))}
 - 9/2272 {Devices for carrying out the processes, e.g. light houses}
 - 9/2273 {Auxiliary lenses and filters}
 - 9/2274 {Light sources particularly adapted therefor}
 - 9/2275 {including the exposition of a substance responsive to a particular radiation}
 - 9/2276 {Development of latent electrostatic images ([per se G03G 15/06](#))}
 - 9/2277 {by other processes, e.g. serigraphy, decalomania}
 - 9/2278 {Application of light absorbing material, e.g. between the luminescent areas}
 - 9/233 . . Manufacture of photoelectric screens or charge-storage screens
 - 9/236 . . Manufacture of magnetic deflecting devices for cathode-ray tubes
 - 9/24 . . Manufacture or joining of vessels, leading-in conductors or bases
 - 9/241 . . {the vessel being for a flat panel display ([H01J 9/261](#) takes precedence; flat discharge lamps [H01J 9/248](#))}
 - 9/242 . . . {Spacers between faceplate and backplate}
 - 9/244 . . {specially adapted for cathode ray tubes ([H01J 9/241](#), [H01J 9/26](#) take precedence)}
 - 9/245 . . {specially adapted for gas discharge tubes or lamps ([H01J 9/241](#), [H01J 9/26](#) take precedence)}
 - 9/247 . . . {specially adapted for gas-discharge lamps}
 - 9/248 {the vessel being flat}
 - 9/26 . . Sealing together parts of vessels
 - 9/261 . . . {the vessel being for a flat panel display (for flat discharge lamps [H01J 9/268](#))}
 - 9/263 . . . {specially adapted for cathode-ray tubes ([H01J 9/261](#) takes precedence)}
 - 9/265 . . . {specially adapted for gas-discharge tubes or lamps ([H01J 9/261](#) takes precedence)}
 - 9/266 {specially adapted for gas-discharge lamps}
 - 9/268 {the vessel being flat}
 - 9/28 . . Manufacture of leading-in conductors
 - 9/30 . . Manufacture of bases
 - 9/32 . . Sealing leading-in conductors
 - 9/323 . . . {Sealing leading-in conductors into a discharge lamp or a gas-filled discharge device}
 - 9/326 {making pinched-stem or analogous seals}
 - 9/34 . . Joining base to vessel
 - 9/36 . . Joining connectors to internal electrode system
 - 9/38 . . Exhausting, degassing, filling, or cleaning vessels
 - 9/385 . . Exhausting vessels
 - 9/39 . . Degassing vessels
 - 9/395 . . Filling vessels
 - 9/40 . . Closing vessels
 - 9/42 . . Measurement or testing during manufacture
 - 9/44 . . Factory adjustment of completed discharge tubes or lamps to comply with desired tolerances
 - 9/445 . . {Aging of tubes or lamps, e.g. by "spot knocking" ([cathode activation H01J 9/045](#))}
 - 9/46 . . Machines having sequentially arranged operating stations
 - 9/48 . . with automatic transfer of workpieces between operating stations
 - 9/50 . . Repairing or regenerating used or defective discharge tubes or lamps
 - 9/505 . . {Regeneration of cathodes}
 - 9/52 . . Recovery of material from discharge tubes or lamps ([H01J 9/50](#) takes precedence)
 - 11/00 Gas-filled discharge tubes with alternating current induction of the discharge, e.g. alternating current plasma display panels [AC-PDP] (circuits or methods for driving PDPs [G09G 3/28](#)); Gas-filled discharge tubes without any main electrode inside the vessel; Gas-filled discharge tubes with at least one main electrode outside the vessel**
- NOTES**
1. When classifying in this group, classification is made in all appropriate places.
 2. In this group, the following term is used with the meaning indicated:
 - "main electrode" means any of a sustain electrode, scan electrode or address electrode.
- 11/10 . . AC-PDPs with at least one main electrode being out of contact with the plasma
 - 11/12 . . with main electrodes provided on both sides of the discharge space
 - 11/14 . . with main electrodes provided only on one side of the discharge space
 - 11/16 . . with main electrodes provided inside or on the side face of the spacers
 - 11/18 . . containing a plurality of independent closed structures for containing the gas, e.g. plasma tube array [PTA] display panels

- 11/20 . Constructional details
- 11/22 . . Electrodes, e.g. special shape, material or configuration
- 11/24 . . . Sustain electrodes or scan electrodes
- 11/26 . . . Address electrodes
- 11/28 . . . Auxiliary electrodes, e.g. priming electrodes or trigger electrodes
- 11/30 . . . Floating electrodes
- 11/32 . . . Disposition of the electrodes
- 11/34 . . Vessels, containers or parts thereof, e.g. substrates
- 11/36 . . . Spacers, barriers, ribs, partitions or the like
- 11/38 . . . Dielectric or insulating layers
- 11/40 . . . Layers for protecting or enhancing the electron emission, e.g. MgO layers
- 11/42 . . . Fluorescent layers
- 11/44 . . . Optical arrangements or shielding arrangements, e.g. filters, black matrices, light reflecting means or electromagnetic shielding means
- 11/46 . . Connecting or feeding means, e.g. leading-in conductors
- 11/48 . . Sealing, e.g. seals specially adapted for leading-in conductors
- 11/50 . . Filling, e.g. selection of gas mixture
- 11/52 . . Means for absorbing or adsorbing the gas mixture, e.g. by gettering
- 11/54 . . Means for exhausting the gas
- 13/00 Discharge tubes with liquid-pool cathodes, e.g. metal-vapour rectifying tubes**
- 13/02 . Details
- 13/04 . . Main electrodes; Auxiliary anodes
- 13/06 . . . Cathodes
- 13/08 characterised by the material
- 13/10 Containers for the liquid pool; Arrangements or mounting thereof
- 13/12 Positioning or moving the cathode spot on the surface of the pool
- 13/14 Cooling, heating, circulating, filtering, or controlling level of the liquid
- 13/16 . . . Anodes; Auxiliary anodes for maintaining the discharge
- 13/18 Cooling or heating of anodes
- 13/20 . . Control electrodes, e.g. grid (for igniting arrangements [H01J 13/34](#))
- 13/22 . . Screens, e.g. for preventing or eliminating arcing-back
- 13/24 . . Vessels; Containers
- 13/242 . . . {characterised by the material}
- 13/244 . . . {characterised by the shape}
- 13/246 . . . {Treatment of, or coating on interior parts of vessel}
- 13/248 . . . {Envelope means outside vessel, i.e. screens, reflectors, filters}
- 13/26 . . Seals between parts of vessels; Seals for leading-in conductors; Leading-in conductors
- 13/263 . . . {Leading-in conductors to the liquid electrode}
- 13/266 . . . {Leading-in conductors to the anode}
- 13/28 . . Selection of substances for gas filling; Means for obtaining the desired pressure within the tube
- 13/30 . . . Means for permitting pumping during operation of the tube
- 13/32 . . Cooling arrangements; Heating arrangements (for cathodes [H01J 13/14](#); for anodes [H01J 13/18](#))
- 13/34 . . Igniting arrangements
- 13/36 . . . having resistive or capacitive igniter
- 13/38 having resistive igniter only
- 13/40 . . . Igniting by movement of a solid electrode
- 13/405 {Interrupting contact with liquid cathode}
- 13/42 . . . Igniting by movement of vessel as a whole, e.g. tilting
- 13/44 . . Devices for preventing or eliminating arcing-back
- 13/46 . . One or more circuit elements structurally associated with the tube
- 13/48 . . Circuit arrangements not adapted to a particular application of the tube and not otherwise provided for
- 13/50 . Tubes having a single main anode
- 13/52 . . with control by one or more intermediate control electrodes
- 13/54 . . with control by igniter, e.g. single-anode ignitron
- 13/56 . Tubes having two or more main anodes
- 13/58 . . with control by one or more intermediate control electrodes
- 15/00 Gas-filled discharge tubes with gaseous cathodes, e.g. plasma cathode**
- 15/02 . Details, e.g. electrode, gas filling, shape of vessel
- 15/04 . . Circuit arrangements not adapted to a particular application of the tube and not otherwise provided for
- 17/00 Gas-filled discharge tubes with solid cathode**
([H01J 25/00](#), [H01J 27/00](#), [H01J 31/00](#) - [H01J 41/00](#) { , [H01J 11/00](#) } take precedence; gas filled spark gaps [H01T](#); Marx converters [H02M 7/26](#))
- 17/005 . {specially adapted as noise generators (electronic circuits for generation of noise currents or voltages [H03B 29/00](#))}
- 17/02 . Details
- 17/04 . . Electrodes; Screens
- 17/06 . . . Cathodes
- 17/063 {Indirectly heated cathodes, e.g. by the discharge itself}
- 17/066 {Cold cathodes}
- 17/08 having mercury or liquid alkali metal deposited on the cathode surface during operation of the tube
- 17/10 . . . Anodes
- 17/12 . . . Control electrodes
- 17/14 . . Magnetic means for controlling the discharge
- 17/16 . . Vessels; Containers
- 17/18 . . Seals between parts of vessels; Seals for leading-in conductors; Leading-in conductors
- 17/183 . . . {Seals between parts of vessel}
- 17/186 . . . {Seals between leading-in conductors and vessel}
- 17/20 . . Selection of substances for gas fillings; Specified operating pressures or temperatures
- 17/22 . . Means for obtaining or maintaining the desired pressure within the tube
- 17/24 . . . Means for absorbing or adsorbing gas, e.g. by gettering
- 17/26 . . . Means for producing, introducing, or replenishing gas or vapour during operation of the tube

17/28	. . Cooling arrangements	19/066 with metals or alloys as an emissive material
17/30	. . Igniting arrangements	19/068 with compounds having metallic conductive properties, e.g. lanthanum boride, as an emissive material
17/32	. . . Igniting by associated radioactive materials or fillings	19/08	. . . Cathodes heated directly by an electric current
17/325 {Current stabilising tubes, e.g. curpistors}	19/10	. . . characterised by the shape
17/34	. . One or more circuit elements structurally associated with the tube	19/12 Supports; Vibration-damping arrangements
17/36	. . Circuit arrangements not adapted to a particular application of the tube and not otherwise provided for	19/14	. . . Cathodes heated indirectly by an electric current; Cathodes heated by electron or ion bombardment
17/38	. Cold-cathode tubes	19/16 Heaters
17/40	. . with one cathode and one anode, e.g. glow tubes, tuning-indicator glow tubes, voltage-stabiliser tubes, voltage-indicator tubes, (cathode-glow lamps H01J 61/04)	19/18 Insulating layer or body located between heater and emissive material
17/42	. . . having one or more probe electrodes, e.g. for potential dividing	19/20 Supports for the emissive material
17/44	. . . having one or more control electrodes	19/22 Dispenser-type cathodes, e.g. L-cathode
17/46 for preventing and then permitting ignition but thereafter having no control	19/24	. . Cold cathodes, e.g. field-emissive cathode
17/48	. . with more than one cathode or anode, e.g. sequence-discharge tube, counting tube, dekatron	19/28	. Non-electron-emitting electrodes; Screens
17/485	. . . {Plasma addressed liquid crystal displays [PALC]}	19/30	. . characterised by the material
17/49	. . . Display panels, e.g. with crossed electrodes {, e.g. making use of direct current (display panels making use of alternating current H01J 11/00)}	19/32	. . Anodes
17/491 {with electrodes arranged side by side and substantially in the same plane, e.g. for displaying alphanumeric characters}	19/34	. . . forming part of the envelope
17/492 {with crossed electrodes}	19/36	. . . Cooling of anodes
17/494 {using sequential transfer of the discharges, e.g. of the self-scan type (addressing circuits therefor G09G 3/29)}	19/38	. . Control electrodes, e.g. grid
17/495 {display panels using sequential transfer of the discharge along dielectric storage elements}	19/40	. . Screens for shielding
17/497 {for several colours}	19/42	. Mounting, supporting, spacing, or insulating of electrodes or of electrode assemblies
17/498 {with a gas discharge space and a post acceleration space for electrons}	19/44	. . Insulation between electrodes or supports within the vacuum space
17/50	. Thermionic-cathode tubes	19/46	. . Mountings for the electrode assembly as a whole
17/52	. . with one cathode and one anode	19/48	. . Mountings for individual electrodes
17/54	. . . having one or more control electrodes	19/50	. . Spacing members extending to the envelope
17/56 for preventing and then permitting ignition, but thereafter having no control	19/52	. . . without fixed connection between spacing member and envelope
17/58	. . with more than one cathode or anode	19/54	. Vessels; Containers; Shields associated therewith
17/60	. . . the discharge paths priming each other in a predetermined sequence, e.g. counting tube	19/56	. . characterised by the material of the vessel or container
17/62	. . . with independent discharge paths controlled by intermediate electrodes, e.g. polyphase rectifier	19/57	. . provided with coatings on the walls thereof; Selection of materials for the coatings
17/64	. Tubes specially designed for switching or modulating in a waveguide, e.g. TR box	19/58	. Seals between parts of vessels
19/00	Details of vacuum tubes of the types covered by group H01J 21/00	19/60	. Seals for leading-in conductors
19/02	. Electron-emitting electrodes; Cathodes	19/62	. Leading-in conductors
19/04	. . Thermionic cathodes	19/64	. Means forming part of the tube for the purpose supporting it
19/06	. . . characterised by the material	19/66	. Means forming part of the tube for the purpose of providing electrical connection to it {(H01J 5/46 - H01J 5/62 take precedence)}
19/062 with alkaline-earth metal oxides, or such oxides used in conjunction with reducing agents, as an emissive material	19/68	. Specified gas introduced into the tube at low pressure, e.g. for reducing or influencing space charge
19/064 with other metal oxides as an emissive material	19/70	. Means for obtaining or maintaining the vacuum, e.g. by gettering
		19/72	. . Tubulations therefor, e.g. for exhausting; Closures therefor
		19/74	. Cooling arrangements (cooling of anodes H01J 19/36)
		19/76	. Means structurally associated with the tube for indicating defects or previous use
		19/78	. One or more circuit elements structurally associated with the tube
		19/80	. . Structurally associated resonator having distributed inductance and capacitance
		19/82	. Circuit arrangements not adapted to a particular application of the tube and not otherwise provided for

21/00	Vacuum tubes (H01J 25/00 , H01J 31/00 - H01J 40/00 , H01J 43/00 , H01J 47/00 , H01J 49/00 take precedence; details of vacuum tubes H01J 19/00)	23/10	<ul style="list-style-type: none"> • • Magnet systems for directing or deflecting the discharge along a desired path, e.g. a spiral path (magnetic focusing arrangements H01J 23/08)
21/02	<ul style="list-style-type: none"> • Tubes with a single discharge path 	23/11	<ul style="list-style-type: none"> • • Means for reducing noise (in electron or ion gun H01J 23/06)
21/04	<ul style="list-style-type: none"> • • without control means, i.e. diodes 	23/12	<ul style="list-style-type: none"> • Vessels; Containers
21/06	<ul style="list-style-type: none"> • • having electrostatic control means only 	23/14	<ul style="list-style-type: none"> • Leading-in arrangements; Seals therefor
21/065	<ul style="list-style-type: none"> • • • {Devices for short wave tubes} 	23/15	<ul style="list-style-type: none"> • • Means for preventing wave energy leakage structurally associated with tube leading-in arrangements, e.g. filters, chokes, attenuating devices
21/08	<ul style="list-style-type: none"> • • • with movable electrode or electrodes 	23/16	<ul style="list-style-type: none"> • Circuit elements, having distributed capacitance and inductance, structurally associated with the tube and interacting with the discharge
21/10	<ul style="list-style-type: none"> • • • with one or more immovable internal control electrodes, e.g. triode, pentode, octode 	23/165	<ul style="list-style-type: none"> • • {Manufacturing processes or apparatus therefore}
21/105	<ul style="list-style-type: none"> • • • • {with microengineered cathode and control electrodes, e.g. Spindt-type} 	23/18	<ul style="list-style-type: none"> • • Resonators
21/12	<ul style="list-style-type: none"> • • • • Tubes with variable amplification factor 	23/20	<ul style="list-style-type: none"> • • • Cavity resonators; Adjustment or tuning thereof
21/14	<ul style="list-style-type: none"> • • • • Tubes with means for concentrating the electron stream, e.g. beam tetrode 	23/207	<ul style="list-style-type: none"> • • • • Tuning of single resonator
21/16	<ul style="list-style-type: none"> • • • with external electrostatic control means and with or without internal control electrodes 	23/213	<ul style="list-style-type: none"> • • • • Simultaneous tuning of more than one resonator, e.g. resonant cavities of a magnetron
21/18	<ul style="list-style-type: none"> • • having magnetic control means; having both magnetic and electrostatic control means 	23/22	<ul style="list-style-type: none"> • • • Connections between resonators, e.g. strapping for connecting resonators of a magnetron
21/20	<ul style="list-style-type: none"> • Tubes with more than one discharge path; Multiple tubes, e.g. double diode, triode-hexode 	23/24	<ul style="list-style-type: none"> • • Slow-wave structures {, e.g. delay systems}
21/22	<ul style="list-style-type: none"> • • with movable electrode or electrodes 	23/26	<ul style="list-style-type: none"> • • • Helical slow-wave structures; Adjustment therefor
21/24	<ul style="list-style-type: none"> • • with variable amplification factor 	23/27	<ul style="list-style-type: none"> • • • • Helix-derived slow-wave structures
21/26	<ul style="list-style-type: none"> • • with means for concentrating the electron stream 	23/28	<ul style="list-style-type: none"> • • • Interdigital slow-wave structures; Adjustment therefor
21/34	<ul style="list-style-type: none"> • Tubes with electrode system arranged or dimensioned so as to eliminate transit-time effect (with flat electrodes H01J 21/36) 	23/30	<ul style="list-style-type: none"> • • • Damping arrangements associated with slow-wave structures, e.g. for suppression of unwanted oscillations
21/36	<ul style="list-style-type: none"> • Tubes with flat electrodes, e.g. disc electrode 	23/34	<ul style="list-style-type: none"> • Circuit arrangements not adapted to a particular application of the tube and not otherwise provided for
23/00	Details of transit-time tubes of the types covered by group H01J 25/00	23/36	<ul style="list-style-type: none"> • Coupling devices having distributed capacitance and inductance, structurally associated with the tube, for introducing or removing wave energy
23/005	<ul style="list-style-type: none"> • {Cooling methods or arrangements (H01J 23/033 takes precedence)} 	23/38	<ul style="list-style-type: none"> • • to or from the discharge
23/02	<ul style="list-style-type: none"> • Electrodes; Magnetic control means; Screens (associated with resonator or delay system H01J 23/16) 	23/40	<ul style="list-style-type: none"> • • to or from the interaction circuit
23/027	<ul style="list-style-type: none"> • • Collectors 	23/42	<ul style="list-style-type: none"> • • • the interaction circuit being a helix or a helix-derived slow-wave structure (H01J 23/44 - H01J 23/48 take precedence)
23/0275	<ul style="list-style-type: none"> • • • {Multistage collectors} 	23/44	<ul style="list-style-type: none"> • • • Rod-type coupling devices (H01J 23/46, H01J 23/48, H01J 23/54 take precedence)
23/033	<ul style="list-style-type: none"> • • • Collector cooling devices 	23/46	<ul style="list-style-type: none"> • • • Loop coupling devices
23/04	<ul style="list-style-type: none"> • • Cathodes 	23/48	<ul style="list-style-type: none"> • • • for linking interaction circuit with coaxial lines; Devices of the coupled helices type (H01J 23/46 takes precedence)
23/05	<ul style="list-style-type: none"> • • • having a cylindrical emissive surface, e.g. cathodes for magnetrons 	23/50	<ul style="list-style-type: none"> • • • • the interaction circuit being a helix or derived from a helix (H01J 23/52 takes precedence)
23/06	<ul style="list-style-type: none"> • • Electron or ion guns 	23/52	<ul style="list-style-type: none"> • • • • the coupled helices being disposed coaxially around one another
23/065	<ul style="list-style-type: none"> • • • producing a solid cylindrical beam (H01J 23/075 takes precedence) 	23/54	<ul style="list-style-type: none"> • • Filtering devices preventing unwanted frequencies or modes to be coupled to, or out of, the interaction circuit; Prevention of high frequency leakage in the environment
23/07	<ul style="list-style-type: none"> • • • producing a hollow cylindrical beam (H01J 23/075 takes precedence) 	25/00	Transit-time tubes, e.g. klystrons, travelling-wave tubes, magnetrons (details of transit-time tubes H01J 23/00 ; particle accelerators H05H)
23/075	<ul style="list-style-type: none"> • • • Magnetron injection guns 	25/005	<ul style="list-style-type: none"> • {Gas-filled transit-time tubes}
23/08	<ul style="list-style-type: none"> • • Focusing arrangements, e.g. for concentrating stream of electrons, for preventing spreading of stream 		
23/083	<ul style="list-style-type: none"> • • • Electrostatic focusing arrangements 		
23/087	<ul style="list-style-type: none"> • • • Magnetic focusing arrangements 		
23/0873	<ul style="list-style-type: none"> • • • • {with at least one axial-field reversal along the interaction space, e.g. P.P.M. focusing} 		
23/0876	<ul style="list-style-type: none"> • • • • {with arrangements improving the linearity and homogeneity of the axial field, e.g. field straightener} 		
23/09	<ul style="list-style-type: none"> • • Electric systems for directing or deflecting the discharge along a desired path, e.g. E-type (focusing arrangements H01J 23/08) 		

- 25/02 . Tubes with electron stream modulated in velocity or density in a modulator zone and thereafter giving up energy in an inducing zone, the zones being associated with one or more resonators
- 25/025 . . {with an electron stream following a helical path}
- 25/04 . . Tubes having one or more resonators, without reflection of the electron stream, and in which the modulation produced in the modulator zone is mainly density modulation, e.g. Heaff tube
- 25/06 . . Tubes having only one resonator, without reflection of the electron stream, and in which the modulation produced in the modulator zone is mainly velocity modulation, e.g. Lüdi-Klystron
- 25/08 . . . with electron stream perpendicular to the axis of the resonator
- 25/10 . . Klystrons, i.e. tubes having two or more resonators, without reflection of the electron stream, and in which the stream is modulated mainly by velocity in the zone of the input resonator
- 25/11 . . . Extended interaction klystrons
- 25/12 . . . with pencil-like electron stream in the axis of the resonators
- 25/14 . . . with tube-like electron stream coaxial with the axis of the resonators
- 25/16 . . . with pencil-like electron stream perpendicular to the axis of the resonators
- 25/18 . . . with radial or disc-like electron stream perpendicular to the axis of the resonators
- 25/20 . . . having special arrangements in the space between resonators, e.g. resistive-wall amplifier tube, space-charge amplifier tube, velocity-jump tube
- 25/22 . . Reflex klystrons, i.e. tubes having one or more resonators, with a single reflection of the electron stream, and in which the stream is modulated mainly by velocity in the modulator zone
- 25/24 . . . in which the electron stream is in the axis of the resonator or resonators and is pencil-like before reflection
- 25/26 . . . in which the electron stream is coaxial with the axis of the resonator or resonators and is tube-like before reflection
- 25/28 . . . in which the electron stream is perpendicular to the axis of the resonator or resonators and is pencil-like before reflection
- 25/30 . . . in which the electron stream is perpendicular to the axis of the resonator or resonators and is radial or disc-like before reflection
- 25/32 . . Tubes with plural reflection, e.g. Coeterier tube
- 25/34 . Travelling-wave tubes; Tubes in which a travelling wave is simulated at spaced gaps
- 25/36 . . Tubes in which an electron stream interacts with a wave travelling along a delay line or equivalent sequence of impedance elements, and without magnet system producing an H-field crossing the E-field
- 25/38 . . . the forward travelling wave being utilised
- 25/40 . . . the backward travelling wave being utilised
- 25/42 . . Tubes in which an electron stream interacts with a wave travelling along a delay line or equivalent sequence of impedance elements, and with a magnet system producing an H-field crossing the E-field (with travelling wave moving completely around the electron space [H01J 25/50](#))
- 25/44 . . . the forward travelling wave being utilised
- 25/46 . . . the backward travelling wave being utilised
- 25/48 . . Tubes in which two electron streams of different velocities interact with one another, e.g. electron-wave tube
- 25/49 . . Tubes using the parametric principle, e.g. for parametric amplification
- 25/50 . Magnetrons, i.e. tubes with a magnet system producing an H-field crossing the E-field (with travelling wave not moving completely around the electron space [H01J 25/42](#); functioning with plural reflection or with reversed cyclotron action [H01J 25/62](#), [H01J 25/64](#))
- 25/52 . . with an electron space having a shape that does not prevent any electron from moving completely around the cathode or guide electrode
- 25/54 . . . having only one cavity or other resonator, e.g. neutrode tubes
- 25/55 Coaxial cavity magnetrons
- 25/56 with interdigital arrangements of anodes, e.g. turbator tube
- 25/58 . . . having a number of resonators; having a composite resonator, e.g. a helix
- 25/587 Multi-cavity magnetrons
- 25/593 Rising-sun magnetrons
- 25/60 . . with an electron space having a shape that prevents any electron from moving completely around the cathode or guide electrode; Linear magnetrons
- 25/61 . Hybrid tubes, i.e. tubes comprising a klystron section and a travelling-wave section
- 25/62 . Strophotrons, i.e. tubes with H-field crossing the E-field and functioning with plural reflection
- 25/64 . Turbine tubes, i.e. tubes with H-field crossing the E-field and functioning with reversed cyclotron action
- 25/66 . Tubes with electron stream crossing itself and thereby interacting or interfering with itself
- 25/68 . Tubes specially designed to act as oscillator with positive grid and retarding field, e.g. for Barkhausen-Kurz oscillators (with secondary emission [H01J 25/76](#))
- 25/70 . . with resonator having distributed inductance with capacitance, e.g. Pintsch tube
- 25/72 . . in which a standing wave or a considerable part thereof is produced along an electrode, e.g. Clavier tube (with resonator having distributed inductance and capacitance [H01J 25/70](#))
- 25/74 . Tubes specially designed to act as transit-time diode oscillators, e.g. monotrons
- 25/76 . Dynamic electron-multiplier tubes, e.g. Farnsworth multiplier tube, multipactor
- 25/78 . Tubes with electron stream modulated by deflection in a resonator
- 27/00 **Ion beam tubes** ([H01J 25/00](#), [H01J 33/00](#), [H01J 37/00](#) take precedence; particle accelerators [H05H](#))
- 27/02 . Ion sources; Ion guns (for examination or processing discharge tubes [H01J 37/08](#); ion sources, ion guns for particle spectrometer or separator tubes [H01J 49/10](#); ion propulsion [F03H 1/00](#))
- 27/022 . . {Details}
- 27/024 . . . {Extraction optics, e.g. grids}
- 27/026 . . {Cluster ion sources}
- 27/028 . . {Negative ion sources}

- 27/04 . . using reflex discharge, e.g. Penning ion sources {(electron bombardment ion sources [H01J 27/08](#))}
- 27/06 . . . without applied magnetic field
- 27/08 . . using arc discharge
- 27/10 . . . Duoplasmatrons {; [Duopigatrons](#)}
- 27/12 provided with an expansion cup
- 27/14 . . . Other arc discharge ion sources using an applied magnetic field
- 27/143 {Hall-effect ion sources with closed electron drift}
- 27/146 {End-Hall type ion sources, wherein the magnetic field confines the electrons in a central cylinder}
- 27/16 . . using high-frequency excitation, e.g. microwave excitation
- 27/18 . . . with an applied axial magnetic field
- 27/20 . . using particle {beam} bombardment, e.g. ionisers
- 27/205 . . . {with electrons, e.g. electron impact ionisation, electron attachment}
- 27/22 . . . Metal ion sources
- 27/24 . . using photo-ionisation, e.g. using laser beam
- 27/26 . . using surface ionisation, e.g. field effect ion sources, thermionic ion sources ([H01J 27/20](#), [H01J 27/24](#) take precedence)
- 29/00 Details of cathode-ray tubes or of electron-beam tubes of the types covered by group [H01J 31/00](#)**
- 29/003 . {Arrangements for eliminating unwanted electromagnetic effects, e.g. demagnetisation arrangements, shielding coils ([H01J 29/06](#), [H01J 29/867](#) take precedence; demagnetisation in general [H01F 13/00](#); circuit arrangements therefor [H04N 9/29](#); screening of apparatus against electric or magnetic fields [H05K 9/00](#))}
- 29/006 . {Arrangements for eliminating unwanted temperature effects}
- 29/02 . Electrodes; Screens; Mounting, supporting, spacing or insulating thereof
- 29/021 . . {arrangements for eliminating interferences in the tube ([H01J 29/484](#) takes precedence)}
- 29/023 . . {secondary-electron emitting electrode arrangements (secondary-emission tubes [H01J 43/00](#))}
- 29/025 . . {Mounting or supporting arrangements for grids ([H01J 29/028](#) takes precedence)}
- 29/026 . . {Mounting or supporting arrangements for charge storage screens not deposited on the frontplate}
- 29/028 . . {Mounting or supporting arrangements for flat panel cathode ray tubes, e.g. spacers particularly relating to electrodes}
- 29/04 . . Cathodes
- 29/06 . . Screens for shielding; Masks interposed in the electron stream
- 29/07 . . . Shadow masks for colour television tubes
- 29/073 {Mounting arrangements associated with shadow masks}
- 29/076 {characterised by the shape or distribution of beam-passing apertures}
- 29/08 . . Electrodes intimately associated with a screen on or from which an image or pattern is formed, picked-up, converted or stored, e.g. backing-plates for storage tubes or collecting secondary electrons
- 29/085 . . . {Anode plates, e.g. for screens of flat panel displays}
- 29/10 . . Screens on or from which an image or pattern is formed, picked up, converted or stored
- 29/12 . . . acting as light valves by shutter operation, e.g. for eidophor
- 29/14 . . . acting by discoloration, e.g. halide screen
- 29/16 . . . Incandescent screens
- 29/18 . . . Luminescent screens
- 29/182 {acting upon the lighting-up of the luminescent material other than by the composition of the luminescent material, e.g. by infra red or UV radiation, heating or electric fields}
- 29/185 {measures against halo-phenomena}
- 29/187 {screens with more than one luminescent material (as mixtures for the treatment of the screens) (for several superimposed luminescent layers [H01J 29/26](#); for adjacent dots or lines of different luminescent material [H01J 29/32](#))}
- 29/20 characterised by the luminescent material
- 29/22 characterised by the binder or adhesive for securing the luminescent material to its support, e.g. vessel
- 29/225 {photosensitive adhesive}
- 29/24 Supports for luminescent material
- 29/26 with superimposed luminescent layers
- 29/28 with protective, conductive or reflective layers
- 29/30 with luminescent material discontinuously arranged, e.g. in dots, in lines
- 29/32 with adjacent dots or lines of different luminescent material, e.g. for colour television
- 29/322 {with adjacent dots}
- 29/325 {with adjacent lines}
- 29/327 {Black matrix materials}
- 29/34 provided with permanent marks or references
- 29/36 . . . Photoelectric screens; Charge-storage screens
- 29/38 not using charge storage, e.g. photo-emissive screen, extended cathode {(electrodes using photo-emission in general [H01J 1/34](#))}
- 29/385 {Photocathodes comprising a layer which modified the wave length of impinging radiation}
- 29/39 Charge-storage screens
- 29/395 {charge-storage grids exhibiting triode effect}
- 29/41 using secondary emission, e.g. for supericonoscope {(electrodes using secondary emission in general [H01J 1/32](#); secondary emission tubes [H01J 43/00](#))}
- 29/413 {for writing and reading of charge pattern on opposite sides of the target, e.g. for superorthicon}
- 29/416 {with a matrix of electrical conductors traversing the target}
- 29/43 using photo-emissive mosaic, e.g. for orthicon, for iconoscope
- 29/435 {with a matrix of conductors traversing the target}

- 29/44 exhibiting internal electric effects caused by particle radiation, e.g. bombardment-induced conductivity {(particle detectors exhibiting internal electric effects G01T 1/26)}
- 29/45 exhibiting internal electric effects caused by electromagnetic radiation, e.g. photoconductive screen, photodielectric screen, photovoltaic screen {(photoconductive layers for electrography G03G 5/00)}
- 29/451 {with photosensitive junctions}
- 29/453 {provided with diode arrays}
- 29/455 {formed on a silicon substrate}
- 29/456 {exhibiting no discontinuities, e.g. consisting of uniform layers}
- 29/458 {pyroelectrical targets; targets for infrared or ultraviolet or X-ray radiations}
- 29/46 Arrangements of electrodes and associated parts for generating or controlling the ray or beam, e.g. electron-optical arrangement {(transit time tubes H01J 23/00, H01J 25/00; X-ray tubes H01J 35/00; beam tubes for examining ions, e.g. electron or ion microscopes, or processing of objects or materials, e.g. electron or ion beam tubes H01J 37/04; electron multipliers H01J 43/04; handling of radiation or particles, e.g. focusing, deviating, not otherwise provided for G21K 1/00)}
- NOTE**
H01J 29/48 takes precedence over groups H01J 29/52 - H01J 29/58.
- 29/462 . . . {arrangements for interrupting the beam during inoperative periods}
- 29/465 . . . {for simultaneous focalisation and deflection of ray or beam}
- 29/467 . . . {Control electrodes for flat display tubes, e.g. of the type covered by group H01J 31/123}
- 29/48 . . . Electron guns
- 29/481 . . . {Electron guns using field-emission, photo-emission, or secondary-emission electron source}
- 29/482 . . . {Electron guns using electron multiplication}
- 29/484 . . . {Eliminating deleterious effects due to thermal effects, electrical or magnetic fields; Preventing unwanted emission (H01J 29/481 and H01J 29/482 take precedence)}
- 29/485 . . . {Construction of the gun or of parts thereof (H01J 29/481, H01J 29/482, H01J 29/484 and H01J 29/487 take precedence)}
- 29/487 . . . {Replacing parts of the gun; Relative adjustment of the electrodes (H01J 29/481 and H01J 29/482 take precedence; vacuum locks H01J 29/865)}
- 29/488 . . . {Schematic arrangements of the electrodes for beam forming; Place and form of the electrodes}
- 29/50 . . . two or more guns in a single vacuum space, e.g. for plural-ray tube (H01J 29/51 takes precedence)
- 29/503 {Three or more guns, the axes of which lay in a common plane}
- 29/506 {guns in delta or circular configuration}
- 29/51 Arrangements for controlling convergence of a plurality of beams {by means of electric field only}
- 29/52 Arrangements for controlling intensity of ray or beam, e.g. for modulation {(H01J 29/467 takes precedence)}
- 29/525 {Digitally controlled systems, e.g. Digisplay}
- 29/54 Arrangements for centring ray or beam {(H01J 29/467 takes precedence)}
- 29/56 Arrangements for controlling cross-section of ray or beam; Arrangements for correcting aberration of beam, e.g. due to lenses {(H01J 29/467 takes precedence)}
- 29/563 {for controlling cross-section}
- 29/566 {for correcting aberration}
- 29/58 Arrangements for focusing or reflecting ray or beam
- 29/585 {in which the transit time of the electrons has to be taken into account}
- 29/60 Mirrors
- 29/62 Electrostatic lenses
- 29/622 {producing fields exhibiting symmetry of revolution}
- 29/624 {co-operating with or closely associated to an electron gun}
- 29/626 {producing fields exhibiting periodic axial symmetry, e.g. multipolar fields}
- 29/628 {co-operating with or closely associated to an electron gun}
- 29/64 Magnetic lenses
- 29/66 using electromagnetic means only
- 29/68 using permanent magnets only
- 29/70 Arrangements for deflecting ray or beam {(H01J 29/467, H01J 29/525 take precedence)}
- 29/701 {Systems for correcting deviation or convergence of a plurality of beams by means of magnetic fields at least}
- 29/702 {Convergence correction arrangements therefor}
- 29/703 {Static convergence systems}
- 29/705 {Dynamic convergence systems}
- 29/706 {Deviation correction devices, i.e. having the same action on each beam}
- 29/707 {Arrangements intimately associated with parts of the gun and co-operating with external magnetic excitation devices}
- 29/708 {in which the transit time of the electrons has to be taken into account}
- 29/72 along one straight line or along two perpendicular straight lines
- 29/74 Deflecting by electric fields only
- 29/76 Deflecting by magnetic fields only
- 29/762 {using saddle coils or printed windings (coils per se H01F)}
- 29/764 {using toroidal windings}
- 29/766 {using a combination of saddle coils and toroidal windings}
- 29/768 {using printed windings (printed windings in general H01F 27/2804; manufacturing printed coils per se H01F 41/04; printed circuits and apparatus or processes for manufacturing printed circuits in general H05K 1/00, e.g. H05K 1/16, and H05K 3/00)}

- 29/78 . . . along a circle, spiral or rotating radial line, e.g. for radar display
- 29/80 . . Arrangements for controlling the ray or beam after passing the main deflection system, e.g. for post-acceleration or post-concentration, for colour switching [{\(H01J 29/701 takes precedence\)}](#)
- 29/803 . . . {for post-acceleration or post-deflection, e.g. for colour switching}
- 29/806 {Electron lens mosaics, e.g. fly's eye lenses, colour selection lenses}
- 29/81 . . . using shadow masks
- 29/82 . . Mounting, supporting, spacing, or insulating electron-optical or ion-optical arrangements
- 29/823 . . . {around the neck of the tube}
- 29/826 {Deflection arrangements}
- 29/84 . Traps for removing or diverting unwanted particles, e.g. negative ions, fringing electrons; Arrangements for velocity or mass selection
- 29/845 . . {by means of magnetic systems}
- 29/86 . Vessels; Containers; Vacuum locks
- 29/861 . . {Vessels or containers characterised by the form or the structure thereof}
- 29/862 . . . {of flat panel cathode ray tubes}
- 29/863 . . {Vessels or containers characterised by the material thereof}
- 29/864 . . {Spacers between faceplate and backplate of flat panel cathode ray tubes}
- 29/865 . . {Vacuum locks}
- 29/866 . . . {Devices for introducing a recording support into the vessel}
- 29/867 . . {Means associated with the outside of the vessel for shielding, e.g. magnetic shields [\(screens for shielding inside the vessel H01J 29/06; magnetic shielding in general H05K 9/00\)}](#)}
- 29/868 . . . {Screens covering the input or output face of the vessel, e.g. transparent anti-static coatings, X-ray absorbing layers}
- 29/87 . . Arrangements for preventing or limiting effects of implosion of vessels or containers
- 29/88 . . provided with coatings on the walls thereof; Selection of materials for the coatings [{\(H01J 29/868 and H01J 29/89 take precedence\)}](#)
- 29/89 . . Optical or photographic arrangements structurally combined {or co-operating} with the vessel [{\(H01J 29/866 and H01J 29/868 take precedence\)}](#)
- 29/892 . . . {using fibre optics}
- 29/894 . . . {Arrangements combined with the vessel for the purpose of image projection on a screen [\(projection arrangements for image reproduction, e.g. using eidophor H04N 5/74\)}](#)}
- 29/896 . . . {Anti-reflection means, e.g. eliminating glare due to ambient light}
- 29/898 . . . {Spectral filters}
- 29/90 . Leading-in arrangements; Seals therefor
- 29/92 . Means forming part of the tube for the purpose of providing electrical connection to it
- 29/925 . . {High voltage anode feedthrough connectors for display tubes}
- 29/94 . Selection of substances for gas fillings; Means for obtaining or maintaining the desired pressure within the tube, e.g. by gettering [{\(exhausting, degassing, gettering of electric discharge tubes in general H01J 9/38\)}](#)
- 29/96 . One or more circuit elements structurally associated with the tube
- 29/98 . Circuit arrangements not adapted to a particular application of the tube and not otherwise provided for
- 31/00 Cathode ray tubes; Electron beam tubes**
[\(H01J 25/00, H01J 33/00, H01J 35/00, H01J 37/00 take precedence; details of cathode ray tubes or of electron beam tubes H01J 29/00\)](#)
- 31/02 . having one or more output electrodes which may be impacted selectively by the ray or beam, and onto, from, or over which the ray or beam may be deflected or de-focused [{\(pulse counting circuits therewith H03K 29/06\)}](#)
- 31/04 . . with only one or two output electrodes [{with only two electrically independant groups or electrodes}](#)
- 31/06 . . with more than two output electrodes, e.g. for multiple switching or counting
- 31/065 . . . {for electrography or electrophotography, for transferring a charge pattern through the faceplate [\(leading-in arrangements H01J 29/90; Lenard tubes H01J 33/00; electrography or electrophotography per se G03C\)}](#)}
- 31/08 . having a screen on or from which an image or pattern is formed, picked up, converted, or stored
- 31/10 . . Image or pattern display tubes, i.e. having electrical input and optical output; Flying-spot tubes for scanning purposes
- 31/12 . . . with luminescent screen
- 31/121 {tubes for oscillography [\(colour display tubes H01J 31/20; cathode ray oscillography G01R 13/20\)}](#)}
- 31/122 {Direct viewing storage tubes without storage grid [\(with storage grid H01J 31/18\)}](#)}
- 31/123 {Flat display tubes}
- 31/124 {using electron beam scanning}
- 31/125 {provided with control means permitting the electron beam to reach selected parts of the screen, e.g. digital selection}
- 31/126 {using line sources}
- 31/127 {using large area or array sources, i.e. essentially a source for each pixel group}
- 31/128 {provided with control means permitting the electron beam to reach selected parts of the screen, e.g. digitally controlled display tubes [\(H01J 31/123 takes precedence\)}](#)}
- 31/14 Magic-eye or analogous tuning indicators [{\(mounting of visual indicators in a radio set H03J 1/04; circuits for timing indicators H03J 3/14\)}](#)}
- 31/15 with ray or beam selectively directed to luminescent anode segments [{\(printing by application of radiation B41J 2/447\)}](#)}
- 31/16 with mask carrying a number of selectively displayable signs, e.g. charactron, numeroscope [{\(tubes with a mask carrying a matrix of openings, a selection of which permits a sign to be displayed H01J 31/128\)}](#)}

- 31/18 with image written by a ray or beam on a grid-like charge-accumulating screen, and with a ray or beam passing through and influenced by this screen before striking the luminescent screen, e.g. direct-view storage tube [{\(charge storage grids exhibiting triode effect H01J 29/395\)}](#)
- 31/20 for displaying images or patterns in two or more colours [{\(circuits for colour television H04N 9/16 - H04N 9/28\)}](#)
- 31/201 {using a colour-selection electrode}
- 31/203 {with more than one electron beam}
- 31/205 {with three electron beams in delta configuration}
- 31/206 {with three coplanar electron beams}
- 31/208 {using variable penetration depth of the electron beam in the luminescent layer, e.g. penetrons}
- 31/22 for stereoscopic displays
- 31/24 with screen acting as light valve by shutter operation, e.g. eidophor [{\(projection arrangements for image reproduction, e.g. using eidophor H04N 5/74\)}](#)
- 31/26 Image pick-up tubes having an input of visible light and electric output [\(tubes without defined electron beams and having a light ray scanning photo-emissive screen H01J 40/20\)](#)
- 31/265 {with light spot scanning}
- 31/28 with electron ray scanning the image screen
- 31/283 {with a target comprising semiconductor junctions}
- 31/286 {correlater tubes}
- 31/30 having regulation of screen potential at anode potential, e.g. iconoscope
- 31/32 Tubes with image amplification section, e.g. image-iconoscope, supericonoscope
- 31/34 having regulation of screen potential at cathode potential, e.g. orthicon
- 31/36 Tubes with image amplification section, e.g. image-orthicon
- 31/38 Tubes with photoconductive screen, e.g. vidicon
- 31/40 having grid-like image screen through which the electron ray passes and by which the ray is influenced before striking the output electrode, i.e. having "triode action"
- 31/42 with image screen generating a composite electron beam which is deflected as a whole past a stationary probe to simulate a scanning effect, e.g. Farnsworth pick-up tube
- 31/44 Tubes with image amplification section
- 31/46 Tubes in which electrical output represents both intensity and colour of image [{\(colour television cameras with only one tube H04N 23/12\)}](#)
- 31/48 Tubes with amplification of output effected by electron multiplier arrangements within the vacuum space
- 31/49 Pick-up adapted for an input of electromagnetic radiation other than visible light and having an electric output, e.g. for an input of X-rays, for an input of infrared radiation
- 31/495 Pick-up tubes adapted for an input of sonic, ultrasonic, or mechanical vibrations and having an electric output
- 31/50 Image-conversion or image-amplification tubes, i.e. having optical, X-ray, or analogous input, and optical output
- 31/501 {with an electrostatic electron optic system [\(H01J 31/52 - H01J 31/56 take precedence\)}](#)}
- 31/502 {with means to interrupt the beam, e.g. shutter for high speed photography [\(circuits using electron-beam shutters G03B 27/725\)}](#)}
- 31/503 {with an electromagnetic electron-optic system [\(H01J 31/52 - H01J 31/56 take precedence\)}](#)}
- 31/505 {flat tubes, e.g. proximity focusing tubes}
- 31/506 {tubes using secondary emission effect}
- 31/507 {using a large number of channels, e.g. microchannel plates}
- 31/508 {Multistage converters}
- 31/52 having grid-like image screen through which the electron ray or beam passes and by which the ray or beam is influenced before striking the luminescent output screen, i.e. having "triode action"
- 31/54 in which the electron ray or beam is reflected by the image input screen on to the image output screen
- 31/56 for converting or amplifying images in two or more colours
- 31/58 Tubes for storage of image or information pattern or for conversion of definition of television or like images, i.e. having electrical input and electrical output [{\(electrostatic memories using electron beam tubes G11C 11/23\)}](#)
- 31/585 {Monoscopes [\(H01J 31/60 takes precedence\)}](#)}
- 31/60 having means for deflecting, either selectively or sequentially, an electron ray on to separate surface elements of the screen [\(by circuitry alone H01J 29/08\)](#)
- 31/62 with separate reading and writing rays
- 31/64 on opposite sides of screen, e.g. for conversion of definition
- 31/66 having means for allowing all but selected cross-section elements of a homogeneous electron beam to reach corresponding elements of the screen, e.g. selectron
- 31/68 in which the information pattern represents two or more colours
- 33/00 Discharge tubes with provision for emergence of electrons or ions from the vessel [{\(irradiation devices G21K\) ; particle accelerators H05H\); Lenard tubes}](#)**
- 33/02 Details [{\(vessels for operation at high tension H01J 5/06\)}](#)
- 33/04 Windows
- 35/00 X-ray tubes**
- 35/02 Details
- 35/025 {X-ray tubes with structurally associated circuit elements}
- 35/04 Electrodes [{; Mutual position thereof; Constructional adaptations therefor}](#)
- 35/045 {Electrodes for controlling the current of the cathode ray, e.g. control grids}
- 35/06 Cathodes
- 35/064 {Details of the emitter, e.g. material or structure [\(H01J 35/065 takes precedence\)}](#)}

- 35/065 {Field emission, photo emission or secondary emission cathodes}
- 35/066 {Details of electron optical components, e.g. cathode cups}
- 35/08 . . . Anodes; Anti cathodes
- 35/10 Rotary anodes; Arrangements for rotating anodes; Cooling rotary anodes
- 35/101 {Arrangements for rotating anodes, e.g. supporting means, means for greasing, means for sealing the axle or means for shielding or protecting the driving}
- 35/1017 {Bearings for rotating anodes}
- 35/1024 {Rolling bearings}
- 35/103 {Magnetic bearings}
- 35/104 {Fluid bearings}
- 35/105 {Cooling of rotating anodes, e.g. heat emitting layers or structures}
- 35/106 {Active cooling, e.g. fluid flow, heat pipes}
- 35/107 {Cooling of the bearing assemblies}
- 35/108 {Substrates for and bonding of emissive target, e.g. composite structures}
- 35/112 {Non-rotating anodes ([H01J 35/12](#) takes precedence)}
- 35/116 {Transmissive anodes (acting as a window [H01J 35/186](#))}
- 35/12 Cooling non-rotary anodes
- 35/13 {Active cooling, e.g. fluid flow, heat pipes}
- 35/14 . . Arrangements for concentrating, focusing, or directing the cathode ray
- 35/147 . . . {Spot size control}
- 35/153 . . . {Spot position control}
- 35/16 . . Vessels; Containers; Shields associated therewith
- 35/165 . . . {joining connectors to the tube}
- 35/18 . . . Windows
- 35/186 {used as targets or X-ray converters}
- 35/20 . . Selection of substances for gas fillings; Means for obtaining or maintaining the desired pressure within the tube, e.g. by gettering
- 35/22 . specially designed for passing a very high current for a very short time, e.g. for flash operation
- 35/24 . Tubes wherein the point of impact of the cathode ray on the anode or anticathode is movable relative to the surface thereof
- 35/26 . . by rotation of the anode or anticathode
- 35/28 . . by vibration, oscillation, reciprocation, or swash-plate motion of the anode or anticathode
- 35/30 . . by deflection of the cathode ray
- 35/305 . . . {by using a rotating X-ray tube in conjunction therewith}
- 35/32 . Tubes wherein the X-rays are produced at or near the end of the tube or a part thereof which tube or part has a small cross-section to facilitate introduction into a small hole or cavity
- 37/00 Discharge tubes with provision for introducing objects or material to be exposed to the discharge, e.g. for the purpose of examination or processing thereof ([H01J 33/00](#), [H01J 40/00](#), [H01J 41/00](#), [H01J 47/00](#), [H01J 49/00](#) take precedence)**
- 37/02 . Details
- 37/023 . . {Means for mechanically adjusting components not otherwise provided for}
- 37/026 . . {Means for avoiding or neutralising unwanted electrical charges on tube components}
- 37/04 . . Arrangements of electrodes and associated parts for generating or controlling the discharge, e.g. electron-optical arrangement or ion-optical arrangement ([H01J 37/32009](#), [H01J 37/32623](#), [H01J 37/3266](#), [H01J 37/32697](#) take precedence; electron or ion-optical systems for localised treatment of objects [H01J 37/3007](#))}
- 37/045 . . . {Beam blanking or chopping, i.e. arrangements for momentarily interrupting exposure to the discharge}
- 37/05 . . . Electron or ion-optical arrangements for separating electrons or ions according to their energy {or mass}(particle separator tubes [H01J 49/00](#))
- 37/06 . . . Electron sources; Electron guns
- 37/061 {Electron guns using electron multiplication}
- 37/063 Geometrical arrangement of electrodes for beam-forming
- 37/065 Construction of guns or parts thereof ([H01J 37/067](#) - [H01J 37/077](#) take precedence)
- 37/067 Replacing parts of guns; Mutual adjustment of electrodes ([H01J 37/073](#) - [H01J 37/077](#) take precedence; vacuum locks [H01J 37/18](#))
- 37/07 Eliminating deleterious effects due to thermal effects or electric or magnetic fields ([H01J 37/073](#) - [H01J 37/077](#) take precedence)
- 37/073 Electron guns using field emission, photo emission, or secondary emission electron sources
- 37/075 Electron guns using thermionic emission from cathodes heated by particle bombardment or by irradiation, e.g. by laser
- 37/077 Electron guns using discharge in gases or vapours as electron sources
- 37/08 . . . Ion sources; Ion guns
- 37/09 . . . Diaphragms; Shields associated with electron or ion-optical arrangements; Compensation of disturbing fields
- 37/10 . . . Lenses
- 37/12 electrostatic
- 37/14 magnetic
- 37/141 Electromagnetic lenses
- 37/1413 {Means for interchanging parts of the lens, e. g. pole pieces within the tube}
- 37/1416 {with superconducting coils}
- 37/143 Permanent magnetic lenses
- 37/145 Combinations of electrostatic and magnetic lenses
- 37/147 . . . Arrangements for directing or deflecting the discharge along a desired path ([H01J 37/045](#) take precedence;) lenses [H01J 37/10](#))
- 37/1471 {for centering, aligning or positioning of ray or beam}
- 37/1472 {Deflecting along given lines}
- 37/1474 {Scanning means}
- 37/1475 {magnetic}
- 37/1477 {electrostatic}
- 37/1478 {Beam tilting means, i.e. for stereoscopy or for beam channelling}

- 37/15 . . . External mechanical adjustment of electron or ion optical components ([H01J 37/067](#), [H01J 37/20](#) take precedence)
- 37/153 . . . Electron-optical or ion-optical arrangements for the correction of image defects, e.g. stigmators
- 37/16 . . Vessels; Containers
- 37/165 . . . {Means associated with the vessel for preventing the generation of or for shielding unwanted radiation, e.g. X-rays}
- 37/18 . . Vacuum locks {; Means for obtaining or maintaining the desired pressure within the vessel}
- 37/185 . . . {Means for transferring objects between different enclosures of different pressure or atmosphere}
- 37/20 . . Means for supporting or positioning the object or the material; Means for adjusting diaphragms or lenses associated with the support
- 37/21 . . Means for adjusting the focus
- 37/22 . . Optical {, image processing} or photographic arrangements associated with the tube
- 37/222 . . . {Image processing arrangements associated with the tube}
- 37/224 . . . {Luminescent screens or photographic plates for imaging; Apparatus specially adapted therefor, e. g. cameras, TV-cameras, photographic equipment or exposure control; Optical subsystems specially adapted therefor, e. g. microscopes for observing image on luminescent screen}
- 37/226 . . . {Optical arrangements for illuminating the object; optical arrangements for collecting light from the object}
- 37/228 {whereby illumination or light collection take place in the same area of the discharge}
- 37/24 . . Circuit arrangements not adapted to a particular application of the tube and not otherwise provided for
- 37/241 . . . {High voltage power supply or regulation circuits}
- 37/242 . . . {Filament heating power supply or regulation circuits ([H01J 37/241](#) takes precedence)}
- 37/243 . . . {Beam current control or regulation circuits ([H01J 37/241](#) takes precedence)}
- 37/244 . . Detectors; Associated components or circuits therefor
- 37/248 . . Components associated with high voltage supply
- 37/252 . . Tubes for spot-analysing by electron or ion beams; Microanalysers
- 37/256 . . using scanning beams
- 37/26 . . Electron or ion microscopes; Electron or ion diffraction tubes
- 37/261 . . {Details}
- 37/263 . . . {Contrast, resolution or power of penetration}
- 37/265 . . . {Controlling the tube; circuit arrangements adapted to a particular application not otherwise provided, e.g. bright-field-dark-field illumination}
- 37/266 . . {Measurement of magnetic or electric fields in the object; Lorentz microscopy (spot analysing [H01J 37/252](#); emission microscopes [H01J 37/285](#); reflecting microscopes [H01J 37/29](#))}
- 37/268 . . . {with scanning beams}
- 37/27 . . Shadow microscopy
- 37/28 . . with scanning beams {([H01J 37/268](#), [H01J 37/292](#), [H01J 37/2955](#) take precedence)}
- 37/285 . . Emission microscopes, e.g. field-emission microscopes
- 37/29 . . Reflection microscopes
- 37/292 . . . {using scanning ray}
- 37/295 . . Electron or ion diffraction tubes
- 37/2955 . . . {using scanning ray}
- 37/30 . . Electron-beam or ion-beam tubes for localised treatment of objects
- 37/3002 . . {Details}
- 37/3005 . . . {Observing the objects or the point of impact on the object}
- 37/3007 . . . {Electron or ion-optical systems}
- 37/301 . . Arrangements enabling beams to pass between regions of different pressure
- 37/302 . . Controlling tubes by external information, e.g. programme control ([H01J 37/304](#) takes precedence)
- 37/3023 . . . {Programme control}
- 37/3026 {Patterning strategy}
- 37/304 . . Controlling tubes by information coming from the objects {or from the beam}, e.g. correction signals
- 37/3045 . . . {Object or beam position registration}
- 37/305 . . for casting, melting, evaporating, or etching
- 37/3053 . . . {for evaporating or etching}
- 37/3056 {for microworking, e. g. etching of gratings or trimming of electrical components}
- 37/31 . . for cutting or drilling
- 37/315 . . for welding
- 37/317 . . for changing properties of the objects or for applying thin layers thereon, e.g. for ion implantation ([H01J 37/36](#) takes precedence)
- 37/3171 . . . {for ion implantation}
- 37/3172 {Maskless patterned ion implantation}
- 37/3174 . . . {Particle-beam lithography, e.g. electron beam lithography}
- 37/3175 {Projection methods, i.e. transfer substantially complete pattern to substrate}
- 37/3177 {Multi-beam, e.g. fly's eye, comb probe}
- 37/3178 . . . {for applying thin layers on objects}
- 37/32 . . Gas-filled discharge tubes (heating by discharge [H05B](#))
- 37/32009 . . {Arrangements for generation of plasma specially adapted for examination or treatment of objects, e.g. plasma sources (plasma generation in general [H05H 1/24](#))}
- 37/32018 . . . {Glow discharge}
- 37/32027 {DC powered}
- 37/32036 {AC powered}
- 37/32045 {Circuits specially adapted for controlling the glow discharge}
- 37/32055 . . . {Arc discharge}
- 37/32064 {Circuits specially adapted for controlling the arc discharge (for plasma torches [H01H 1/36](#))}
- 37/32073 . . . {Corona discharge}
- 37/32082 . . . {Radio frequency generated discharge ([H01J 37/32357](#), [H01J 37/32366](#), [H01J 37/32394](#) and [H01J 37/32403](#) take precedence)}

37/32091	{the radio frequency energy being capacitively coupled to the plasma}	37/32486	{Means for reducing recombination coefficient}
37/321	{the radio frequency energy being inductively coupled to the plasma}	37/32495	{Means for protecting the vessel against plasma}
37/3211	{Antennas, e.g. particular shapes of coils}	37/32504	{Means for preventing sputtering of the vessel}
37/32119	{Windows}	37/32513	{Sealing means, e.g. sealing between different parts of the vessel}
37/32128	{using particular waveforms, e.g. polarised waves}	37/32522	{Temperature}
37/32137	{controlling of the discharge by modulation of energy}	37/32532	{Electrodes}
37/32146	{Amplitude modulation, includes pulsing}	37/32541	{Shape}
37/32155	{Frequency modulation}	37/3255	{Material}
37/32165	{Plural frequencies}	37/32559	{Protection means, e.g. coatings}
37/32174	{Circuits specially adapted for controlling the RF discharge}	37/32568	{Relative arrangement or disposition of electrodes; moving means}
37/32183	{Matching circuits}	37/32577	{Electrical connecting means}
37/32192	{Microwave generated discharge (H01J 37/32357 , H01J 37/32366 , H01J 37/32394 , H01J 37/32403 take precedence)}	37/32587	{Triode systems}
37/32201	{Generating means}	37/32596	{Hollow cathodes}
37/32211	{Means for coupling power to the plasma}	37/32605	{Removable or replaceable electrodes or electrode systems}
37/3222	{Antennas}	37/32614	{Consumable cathodes for arc discharge}
37/32229	{Waveguides}	37/32623	{Mechanical discharge control means}
37/32238	{Windows}	37/32633	{Baffles}
37/32247	{Resonators}	37/32642	{Focus rings}
37/32256	{Tuning means}	37/32651	{Shields, e.g. dark space shields, Faraday shields}
37/32266	{Means for controlling power transmitted to the plasma}	37/3266	{Magnetic control means}
37/32275	{Microwave reflectors}	37/32669	{Particular magnets or magnet arrangements for controlling the discharge}
37/32284	{Means for controlling or selecting resonance mode}	37/32678	{Electron cyclotron resonance}
37/32293	{using particular waveforms, e.g. polarised waves}	37/32688	{Multi-cusp fields}
37/32302	{Plural frequencies}	37/32697	{Electrostatic control}
37/32311	{Circuits specially adapted for controlling the microwave discharge}	37/32706	{Polarising the substrate}
37/32321	{Discharge generated by other radiation (H01J 37/32055 , H01J 37/32073 , H01J 37/32082 , H01J 37/32192 , H01J 37/32348 take precedence)}	37/32715	{Workpiece holder}
37/3233	{using charged particles}	37/32724	{Temperature}
37/32339	{using electromagnetic radiation}	37/32733	{Means for moving the material to be treated}
37/32348	{Dielectric barrier discharge}	37/32743	{for introducing the material into processing chamber}
37/32357	{Generation remote from the workpiece, e.g. down-stream}	37/32752	{for moving the material across the discharge}
37/32366	{Localised processing}	37/32761	{Continuous moving}
37/32376	{Scanning across large workpieces}	37/3277	{of continuous material}
37/32385	{Treating the edge of the workpieces}	37/32779	{of batches of workpieces}
37/32394	{Treating interior parts of workpieces}	37/32788	{for extracting the material from the process chamber}
37/32403	{Treating multiple sides of workpieces, e.g. 3D workpieces}	37/32798	{Further details of plasma apparatus not provided for in groups H01J 37/3244 - H01J 37/32788 ; special provisions for cleaning or maintenance of the apparatus}
37/32412	{Plasma immersion ion implantation}	37/32807	{Construction (includes replacing parts of the apparatus)}
37/32422	{Arrangement for selecting ions or species in the plasma}	37/32816	{Pressure}
37/32431	{Constructional details of the reactor}	37/32825	{Working under atmospheric pressure or higher}
37/3244	{Gas supply means}	37/32834	{Exhausting}
37/32449	{Gas control, e.g. control of the gas flow}	37/32844	{Treating effluent gases}
37/32458	{Vessel}	37/32853	{Hygiene}
37/32467	{Material}	37/32862	{ <i>In situ</i> cleaning of vessels and/or internal parts}
37/32477	{characterised by the means for protecting vessels or internal parts, e.g. coatings}	37/32871	{Means for trapping or directing unwanted particles}
		37/3288	{Maintenance}

- 37/32889 {Connection or combination with other apparatus}
- 37/32899 {Multiple chambers, e.g. cluster tools}
- 37/32908 {Utilities}
- 37/32917 . . {Plasma diagnostics}
- 37/32926 . . . {Software, data control or modelling}
- 37/32935 . . . {Monitoring and controlling tubes by information coming from the object and/or discharge}
- 37/32944 {Arc detection}
- 37/32954 {Electron temperature measurement}
- 37/32963 {End-point detection}
- 37/32972 {Spectral analysis}
- 37/32981 {Gas analysis}
- 37/3299 . . . {Feedback systems}
- 37/34 . . . operating with cathodic sputtering ([H01J 37/36](#) takes precedence ; methods of cathodic sputtering [C23C 14/34](#))
- 37/3402 {using supplementary magnetic fields}
- 37/3405 {Magnetron sputtering}
- 37/3408 {Planar magnetron sputtering}
- 37/3411 . . . {Constructional aspects of the reactor}
- 37/3414 {Targets}
- 37/3417 {Arrangements}
- 37/342 {Hollow targets}
- 37/3423 {Shape}
- 37/3426 {Material}
- 37/3429 {Plural materials}
- 37/3432 {Target-material dispenser}
- 37/3435 {Target holders (includes backing plates and endblocks)}
- 37/3438 {Electrodes other than cathode}
- 37/3441 {Dark space shields}
- 37/3444 {Associated circuits}
- 37/3447 {Collimators, shutters, apertures}
- 37/345 {Magnet arrangements in particular for cathodic sputtering apparatus (material of magnets or magnets in general [H01F 1/00](#), [H01F 7/00](#))}
- 37/3452 {Magnet distribution}
- 37/3455 {Movable magnets}
- 37/3458 {Electromagnets in particular for cathodic sputtering apparatus (electromagnets in general [H01F 7/06](#))}
- 37/3461 {Means for shaping the magnetic field, e.g. magnetic shunts}
- 37/3464 . . . {Operating strategies}
- 37/3467 {Pulsed operation, e.g. HIPIMS}
- 37/347 {Thickness uniformity of coated layers or desired profile of target erosion}
- 37/3473 {Composition uniformity or desired gradient}
- 37/3476 . . . {Testing and control}
- 37/3479 {Detecting exhaustion of target material}
- 37/3482 {Detecting or avoiding eroding through}
- 37/3485 {Means for avoiding target poisoning}
- 37/3488 . . . {Constructional details of particle beam apparatus not otherwise provided for, e.g. arrangement, mounting, housing, environment; special provisions for cleaning or maintenance of the apparatus}
- 37/3491 {Manufacturing of targets}
- 37/3494 {Adaptation to extreme pressure conditions}
- 37/3497 {Temperature of target}
- 37/36 . . . for cleaning surfaces while plating with ions of materials introduced into the discharge, e.g. introduced by evaporation ({[condensing of electrically charged vapour onto a surface for covering materials with metals C23C 14/32](#)})
- 40/00 Photoelectric discharge tubes not involving the ionisation of a gas ([H01J 49/00](#) takes precedence)**
- 40/02 . Details
- 40/04 . . Electrodes
- 40/06 . . . Photo-emissive cathodes
- 40/08 . . Magnetic means for controlling discharge
- 40/10 . . Selection of substances for gas fillings
- 40/12 . . One or more circuit elements structurally associated with the tube
- 40/14 . . Circuit arrangements not adapted to a particular application of the tube and not otherwise provided for
- 40/16 . having photo- emissive cathode, e.g. alkaline photoelectric cell ([operating with secondary emission H01J 43/00](#))
- 40/18 . . with luminescent coatings for influencing the sensitivity of the tube, e.g. by converting the input wavelength
- 40/20 . . wherein a light-ray scans a photo-emissive screen
- 41/00 Discharge tubes for measuring pressure of introduced gas {or for detecting presence of gas}; Discharge tubes for evacuation by diffusion of ions**
- 41/02 . Discharge tubes for measuring pressure of introduced gas {or for detecting presence of gas}
- 41/04 . . with ionisation by means of thermionic cathodes
- 41/06 . . with ionisation by means of cold cathodes
- 41/08 . . with ionisation by means of radioactive substances, e.g. alphasources
- 41/10 . . of particle spectrometer type ([particle spectrometers per se H01J 49/00](#))
- 41/12 . Discharge tubes for evacuating by diffusion of ions, e.g. ion pumps, getter ion pumps
- 41/14 . . with ionisation by means of thermionic cathodes
- 41/16 . . . using gettering substances
- 41/18 . . with ionisation by means of cold cathodes
- 41/20 . . . using gettering substances
- 43/00 Secondary-emission tubes; Electron-multiplier tubes ([dynamic electron-multiplier tubes H01J 25/76](#))**
- 43/02 . Tubes in which one or a few electrodes are secondary-electron emitting electrodes
- 43/025 . . {Circuits therefor}
- 43/04 . Electron multipliers ({[if forming part of electron gun H01J 3/023](#)})
- 43/045 . . {Position sensitive electron multipliers}
- 43/06 . . Electrode arrangements
- 43/08 . . . Cathode arrangements ([construction of photo cathodes H01J 40/06](#), [H01J 40/16](#), [H01J 47/00](#), [H01J 49/08](#))
- 43/10 . . . Dynodes ([H01J 43/24](#), [H01J 43/26](#) take precedence)
- 43/12 . . . Anode arrangements
- 43/14 . . . Control of electron beam by magnetic field
- 43/16 . . . Electrode arrangements using essentially one dynode
- 43/18 . . . Electrode arrangements using essentially more than one dynode

- 43/20 Dynodes consisting of sheet material, e.g. plane, bent
- 43/22 Dynodes consisting of electron-permeable material, e.g. foil, grid, tube, venetian blind
- 43/24 Dynodes having potential gradient along their surfaces
- 43/243 {Dynodes consisting of a piling-up of channel-type dynode plates}
- 43/246 {Microchannel plates [MCP] (image amplification tubes using MCP [H01J 31/507](#))}
- 43/26 Box dynodes
- 43/28 . . Vessels {, e.g. wall of the tube}; Windows; Screens; Suppressing undesired discharges or currents
- 43/30 . . Circuit arrangements not adapted to a particular application of the tube and not otherwise provided for
- 45/00 Discharge tubes functioning as thermionic generators** {(structural combination of fuel element with thermoelectric element [G21C 3/40](#); nuclear power plants using thermionic converters [G21D 7/04](#); structural combination of a radioactive source with a thermionic converter, e.g. radioisotope batteries [G21H 1/10](#); generators in which thermal or kinetic energy is converted into electrical energy by ionisation of a fluid and removal of the charge therefrom [H02N 3/00](#))}
- 47/00 Tubes for determining the presence, intensity, density or energy of radiation or particles** ({discharge tubes using igniting by associated radioactive materials or fillings, e.g. current stabilising tubes [H01J 17/32](#)}; photoelectric discharge tubes not involving the ionisation of a gas [H01J 40/00](#) {; discharge tubes for measuring the pressure, partial pressure of introduced gas or for detecting presence of gas [H01J 41/02](#); ionisation chambers using a solid dielectric [G01T 3/008](#)})
- 47/001 . {Details}
- 47/002 . . {Vessels or containers}
- 47/003 . . . {using tissue-equivalent materials}
- 47/004 . . . {Windows permeable to X-rays, gamma-rays, or particles (windows for discharge tubes with provision for emergence of electrons or ions from the vessel [H01J 33/04](#); windows for X-ray tubes [H01J 35/18](#))}
- 47/005 . . {Gas fillings ([H01J 47/12](#) takes precedence); Maintaining the desired pressure within the tube}
- 47/006 . . . {Tissue equivalent gas fillings}
- 47/007 . {Flash detectors}
- 47/008 . {Drift detectors}
- 47/02 . Ionisation chambers
- 47/022 . . {Calibration thereof}
- 47/024 . . {Well-type ionisation chambers}
- 47/026 . . {Gas flow ionisation chambers}
- 47/028 . . {using a liquid dielectric}
- 47/04 . . Capacitive ionisation chambers, e.g. the electrodes of which are used as electrometers
- 47/06 . Proportional counter tubes
- 47/062 . . {Multiwire proportional counter tubes}
- 47/065 . . {Well-type proportional counter tubes}
- 47/067 . . {Gas flow proportional counter tubes}
- 47/08 . Geiger-Müller counter tubes {(gas filling with very short deionisation times [H01J 17/64](#), [H01T](#))}
- 47/10 . Spark counters ([H01J 47/14](#) takes precedence; spark gaps [H01T](#))
- 47/12 . Neutron detector tubes, e.g. BF₃ tubes
- 47/1205 . . {using nuclear reactions of the type (n, alpha) in solid materials, e.g. Boron-10 (n,alpha) Lithium-7, Lithium-6 (n, alpha)Hydrogen-3}
- 47/1211 . . . {Ionisation chambers}
- 47/1216 {Gamma compensated}
- 47/1222 . . . {Proportional counters}
- 47/1227 . . {Fission detectors}
- 47/1233 . . . {Ionisation chambers}
- 47/1238 . . . {Counters}
- 47/1244 {Multiwire counters}
- 47/125 . . {Helium ionisation detectors}
- 47/1255 . . . {Ionisation chambers}
- 47/1261 . . . {Counters}
- 47/1266 {Multi-wire counters}
- 47/1272 . . {BF₃ tubes}
- 47/1277 . . {Light-nuclei-recoil ionisation detectors, e.g. using protons, alpha-particles}
- 47/1283 . . . {Ionisation chambers}
- 47/1288 . . . {Counters}
- 47/1294 {Multi-wire counters}
- 47/14 . Parallel electrode spark or streamer chambers; Wire spark or streamer chambers {(circuit arrangements with multi-wire or parallel-plate chambers for recording of movements or tracks of particles [G01T 5/12](#))}
- 47/16 . . characterised by readout of each individual wire
- 47/18 . . . the readout being electrical ([H01J 47/20](#) takes precedence)
- 47/20 . . . the readout employing electrical or mechanical delay lines, e.g. magnetostrictive delay lines
- 47/22 . . characterised by another type of readout
- 47/24 . . . the readout being acoustical
- 47/26 . . . the readout being optical
- 49/00 Particle spectrometers or separator tubes**
- NOTE**
- In classifying particle separators, no distinction is made between spectrometry and spectrography, the difference being only in the manner of detection which in the first case is electrical and in the second case is by means of a photographic film.
- 49/0004 . {Imaging particle spectrometry}
- 49/0009 . {Calibration of the apparatus}
- 49/0013 . {Miniaturised spectrometers, e.g. having smaller than usual scale, integrated conventional components}
- 49/0018 . . {Microminiaturised spectrometers, e.g. chip-integrated devices, Micro-Electro-Mechanical Systems [MEMS]}
- 49/0022 . {Portable spectrometers, e.g. devices comprising independent power supply, constructional details relating to portability (small scale devices [per se](#) [H01J 49/0013](#) and [H01J 49/0018](#))}
- 49/0027 . {Methods for using particle spectrometers}
- 49/0031 . . {Step by step routines describing the use of the apparatus ([H01J 49/0081](#) takes precedence)}

- 49/0036 . . {Step by step routines describing the handling of the data generated during a measurement}
- 49/004 . {Combinations of spectrometers, tandem spectrometers, e.g. MS/MS, MSn}
- 49/0045 . . {characterised by the fragmentation or other specific reaction}
- 49/005 . . . {by collision with gas, e.g. by introducing gas or by accelerating ions with an electric field}
- 49/0054 . . . {by an electron beam, e.g. electron impact dissociation, electron capture dissociation}
- 49/0059 . . . {by a photon beam, photo-dissociation}
- 49/0063 . . . {by applying a resonant excitation voltage}
- 49/0068 . . . {by collision with a surface, e.g. surface induced dissociation}
- 49/0072 . . . {by ion/ion reaction, e.g. electron transfer dissociation, proton transfer dissociation}
- 49/0077 . . . {specific reactions other than fragmentation}
- 49/0081 . . {Tandem in time, i.e. using a single spectrometer}
- 49/0086 . . {Accelerator mass spectrometers}
- 49/009 . . {Spectrometers having multiple channels, parallel analysis}
- 49/0095 . {Particular arrangements for generating, introducing or analyzing both positive and negative analyte ions (ion/ion reactions [H01J 49/0072](#))}
- 49/02 . Details
- 49/022 . . {Circuit arrangements, e.g. for generating deviation currents or voltages ([regulating electric or magnetic variables in general, e.g. current, magnetic field G05F](#)); Components associated with high voltage supply ([high voltage supply per se H02M](#))}
- 49/025 . . {Detectors specially adapted to particle spectrometers ([data acquisition H01J 49/0036; detectors per se G01T, e.g. G01T 1/28, G01T 1/29](#))}
- 49/027 . . . {detecting image current induced by the movement of charged particles ([H01J 49/38 takes precedence](#))}
- 49/04 . . Arrangements for introducing or extracting samples to be analysed, e.g. vacuum locks; Arrangements for external adjustment of electron- or ion-optical components
- 49/0404 . . . {Capillaries used for transferring samples or ions ([electrospray nozzles H01J 49/167](#))}
- 49/0409 . . . {Sample holders or containers ([containers for retaining a material to be analyzed, B01L 3/50, for DNA, C12Q 1/6834, for biological materials, G01N 33/543](#))}
- 49/0413 {for automated handling}
- 49/0418 {for laser desorption, e.g. matrix-assisted laser desorption/ionisation [MALDI] plates or surface enhanced laser desorption/ionisation [SELDI] plates}
- 49/0422 . . . {for gaseous samples ([interfaces to gas chromatographs G01N 30/7206](#))}
- 49/0427 {using a membrane permeable to gases}
- 49/0431 . . . {for liquid samples ([interfaces to liquid chromatographs G01N 30/7233](#))}
- 49/0436 {using a membrane permeable to liquids}
- 49/044 {with means for preventing droplets from entering the analyzer; Desolvation of droplets}
- 49/0445 {with means for introducing as a spray, a jet or an aerosol ([electrospray ion sources H01J 49/165](#))}
- 49/045 {with means for using a nebulising gas, i.e. pneumatically assisted}
- 49/0454 {with means for vaporising using mechanical energy, e.g. by ultrasonic vibrations}
- 49/0459 . . . {for solid samples}
- 49/0463 {Desorption by laser or particle beam, followed by ionisation as a separate step ([sample holder per se H01J 49/0418](#))}
- 49/0468 . . . {with means for heating or cooling the sample}
- 49/0472 {with means for pyrolysis}
- 49/0477 {using a hot fluid}
- 49/0481 {with means for collisional cooling}
- 49/0486 {with means for monitoring the sample temperature}
- 49/049 {with means for applying heat to desorb the sample; Evaporation}
- 49/0495 . . . {Vacuum locks; Valves ([valves per se F16K](#))}
- 49/06 . . Electron- or ion-optical arrangements
- 49/061 . . . {Ion deflecting means, e.g. ion gates}
- 49/062 . . . {Ion guides ([linear ion traps performing mass selection H01J 49/4225, mass filters H01J 49/421](#))}
- 49/063 {Multipole ion guides, e.g. quadrupoles, hexapoles}
- 49/065 {having stacked electrodes, e.g. ring stack, plate stack}
- 49/066 {Ion funnels}
- 49/067 . . . {Ion lenses, apertures, skimmers}
- 49/068 . . . {Mounting, supporting, spacing, or insulating electrodes}
- 49/08 . . Electron sources, e.g. for generating photo-electrons, secondary electrons or Auger electrons
- 49/10 . . Ion sources; Ion guns
- 49/102 . . . {using reflex discharge, e.g. Penning ion sources}
- 49/105 . . . {using high-frequency excitation, e.g. microwave excitation, Inductively Coupled Plasma [ICP]}
- 49/107 . . . {Arrangements for using several ion sources}
- 49/12 . . . using an arc discharge, e.g. of the duoplasmatron type
- 49/123 {Duoplasmatrons}
- 49/126 {Other arc discharge ion sources using an applied magnetic field}
- 49/14 . . . using particle bombardment, e.g. ionisation chambers
- 49/142 {using a solid target which is not previously vapourised}
- 49/145 {using chemical ionisation}
- 49/147 {with electrons, e.g. electron impact ionisation, electron attachment ([H01J 49/145 takes precedence](#))}
- 49/16 . . . using surface ionisation, e.g. field-, thermionic- or photo-emission
- 49/161 {using photoionisation, e.g. by laser}
- 49/162 {Direct photo-ionisation, e.g. single photon or multi-photon ionisation}
- 49/164 {Laser desorption/ionisation, e.g. matrix-assisted laser desorption/ionisation [MALDI] ([sample holders H01J 49/0418](#))}
- 49/165 {Electrospray ionisation}

- 49/167 {Capillaries and nozzles specially adapted therefor; (electrostatic spraying [per se B05B 5/00](#))}
- 49/168 {field ionisation, e.g. corona discharge (atmospheric pressure corona discharge [per se H01T 19/00](#))}
- 49/18 . . . using spark ionisation
- 49/20 . . Magnetic deflection
- 49/22 . . Electrostatic deflection
- 49/24 . . Vacuum systems, e.g. maintaining desired pressures
- 49/26 . Mass spectrometers or separator tubes
- 49/28 . . Static spectrometers
- 49/282 . . . {using electrostatic analysers}
- 49/284 . . . {using electrostatic and magnetic sectors with simple focusing, e.g. with parallel fields such as Aston spectrometer}
- 49/286 {with energy analysis, e.g. Castaing filter (in cathode-ray or electron-beam tubes [H01J 29/84](#); electron- or ion-optical arrangements for separating electrons or ions from an analysing or processing beam [H01J 37/05](#); micro- or spot-analysing tubes [H01J 37/252](#))}
- 49/288 {using crossed electric and magnetic fields perpendicular to the beam, e.g. Wien filter}
- 49/30 . . . using magnetic analysers {, e.g. Dempster spectrometer}
- 49/305 {with several sectors in tandem}
- 49/32 . . . using double focusing
- 49/322 {with a magnetic sector of 90 degrees, e.g. Mattauch-Herzog type}
- 49/324 {with an electrostatic section of 90 degrees, e.g. Nier-Johnson type}
- 49/326 {with magnetic and electrostatic sectors of 90 degrees}
- 49/328 {with a cycloidal trajectory by using crossed electric and magnetic fields, e.g. trochoidal type}
- 49/34 . . Dynamic spectrometers
- 49/36 . . . Radio frequency spectrometers, e.g. Bennett-type spectrometers, Redhead-type spectrometers
- 49/38 Omegatrons {; using ion cyclotron resonance}
- 49/40 . . . Time-of-flight spectrometers ([H01J 49/36](#) takes precedence)
- 49/401 {characterised by orthogonal acceleration, e.g. focusing or selecting the ions, pusher electrode}
- 49/403 {characterised by the acceleration optics and/or the extraction fields}
- 49/405 {characterised by the reflectron, e.g. curved field, electrode shapes}
- 49/406 {with multiple reflections}
- 49/408 {with multiple changes of direction, e.g. by using electric or magnetic sectors, closed-loop time-of-flight}
- 49/42 . . . Stability-of-path spectrometers, e.g. monopole, quadrupole, multipole, farvitrons
- 49/4205 {Device types}
- 49/421 {Mass filters, i.e. deviating unwanted ions without trapping}
- 49/4215 {Quadrupole mass filters ([H01J 49/4225](#) takes precedence)}
- 49/422 {Two-dimensional RF ion traps (ion guides without mass selection [H01J 49/062](#))}
- 49/4225 {Multipole linear ion traps, e.g. quadrupoles, hexapoles}
- 49/423 {with radial ejection}
- 49/4235 {Stacked rings or stacked plates}
- 49/424 {Three-dimensional ion traps, i.e. comprising end-cap and ring electrodes}
- 49/4245 {Electrostatic ion traps ([H01J 49/422](#) takes precedence)}
- 49/425 {with a logarithmic radial electric potential, e.g. orbitraps}
- 49/4255 {with particular constructional features}
- 49/426 {Methods for controlling ions}
- 49/4265 {Controlling the number of trapped ions; preventing space charge effects}
- 49/427 {Ejection and selection methods}
- 49/4275 {Applying a non-resonant auxiliary oscillating voltage, e.g. parametric excitation}
- 49/428 {Applying a notched broadband signal}
- 49/4285 {Applying a resonant signal, e.g. selective resonant ejection matching the secular frequency of ions ([H01J 49/429](#), [H01J 49/428](#) take precedence)}
- 49/429 {Scanning an electric parameter, e.g. voltage amplitude or frequency}
- 49/4295 {Storage methods}
- 49/44 . . Energy spectrometers, e.g. alpha-, beta-spectrometers
- 49/443 . . {Dynamic spectrometers}
- 49/446 . . . {Time-of-flight spectrometers}
- 49/46 . . Static spectrometers
- 49/463 . . . {using static magnetic fields}
- 49/466 . . . {using crossed electric and magnetic fields perpendicular to the beam, e.g. Wien filter ([see also H01J 49/288](#))}
- 49/48 . . . using electrostatic analysers, e.g. cylindrical sector, Wien filter
- 49/482 {with cylindrical mirrors}
- 49/484 {with spherical mirrors}
- 49/486 {with plane mirrors, i.e. uniform field}
- 49/488 {with retarding grids}

Discharge lamps

- 61/00 Gas-discharge or vapour-discharge lamps (arc lamps with consumable electrodes [H05B](#); electroluminescent lamps [H05B](#))**
- 61/02 . Details
- 61/025 . . {Associated optical elements}
- 61/04 . . Electrodes ([for igniting H01J 61/54](#)); Screens; Shields
- 61/045 . . . {Thermic screens or reflectors ([heat-reflecting coatings on the wall of the vessel H01J 61/35](#))}
- 61/06 . . . Main electrodes
- 61/067 for low-pressure discharge lamps
- 61/0672 {characterised by the construction of the electrode}
- 61/0675 {characterised by the material of the electrode}

- 61/0677 {characterised by the electron emissive material}
- 61/073 for high-pressure discharge lamps
- 61/0732 {characterised by the construction of the electrode}
- 61/0735 {characterised by the material of the electrode}
- 61/0737 {characterised by the electron emissive material}
- 61/09 Hollow cathodes
- 61/10 . . . Shields, screens, or guides for influencing the discharge
- 61/103 {Shields, screens or guides arranged to extend the discharge path (H01J 61/106 takes precedence)}
- 61/106 {using magnetic means}
- 61/12 . . Selection of substances for gas fillings; Specified operating pressure or temperature
- 61/125 . . . {having an halogenide as principal component}
- 61/14 . . . having one or more carbon compounds as the principal constituents
- 61/16 . . . having helium, argon, neon, krypton, or xenon as the principle constituent
- 61/18 . . . having a metallic vapour as the principal constituent
- 61/20 mercury vapour
- 61/22 vapour of an alkali metal
- 61/24 . . Means for obtaining or maintaining the desired pressure within the vessel
- 61/26 . . . Means for absorbing or adsorbing gas, e.g. by gettering; Means for preventing blackening of the envelope
- 61/28 . . . Means for producing, introducing, or replenishing gas or vapour during operation of the lamp
- 61/30 . . Vessels; Containers
- 61/302 . . . {characterised by the material of the vessel}
- 61/305 . . . {Flat vessels or containers}
- 61/307 {with folded elongated discharge path}
- 61/32 . . . Special longitudinal shape, e.g. for advertising purposes {(H01J 61/305 takes precedence)}
- 61/322 {Circular lamps}
- 61/325 {U-shaped lamps}
- 61/327 {"Compact"-lamps, i.e. lamps having a folded discharge path}
- 61/33 . . . Special shape of cross-section, e.g. for producing cool spot
- 61/34 . . . Double-wall vessels or containers
- 61/35 . . . provided with coatings on the walls thereof; Selection of materials for the coatings (using coloured coatings H01J 61/40; using luminescent coatings H01J 61/42)
- 61/36 . . Seals between parts of vessels; Seals for leading-in conductors; Leading-in conductors
- 61/361 . . . {Seals between parts of vessel}
- 61/363 {End-disc seals or plug seals}
- 61/365 {Annular seals disposed between the ends of the vessel (H01J 61/363 takes precedence)}
- 61/366 . . . {Seals for leading-in conductors}
- 61/368 {Pinched seals or analogous seals}
- 61/38 . . Devices for influencing the colour or wavelength of the light
- 61/40 . . . by light filters; by coloured coatings in or on the envelope
- 61/42 . . . by transforming the wavelength of the light by luminescence
- 61/44 Devices characterised by the luminescent material
- 61/46 Devices characterised by the binder or other non-luminescent constituent of the luminescent material, e.g. for obtaining desired pouring or drying properties
- 61/48 Separate coatings of different luminous materials
- 61/50 . . Auxiliary parts or solid material within the envelope for reducing risk of explosion upon breakage of the envelope, e.g. for use in mines
- 61/52 . . Cooling arrangements; Heating arrangements; Means for circulating gas or vapour within the discharge space {(heating or cooling arrangements to promote ionisation for starting H01J 61/54)}
- 61/523 . . . {Heating or cooling particular parts of the lamp}
- 61/526 {heating or cooling of electrodes}
- 61/54 . . Igniting arrangements, e.g. promoting ionisation for starting
- 61/541 . . . {using a bimetal switch}
- 61/542 {and an auxiliary electrode inside the vessel}
- 61/544 {and an auxiliary electrode outside the vessel}
- 61/545 . . . {using an auxiliary electrode inside the vessel (H01J 61/542 takes precedence)}
- 61/547 . . . {using an auxiliary electrode outside the vessel (H01J 61/544 takes precedence)}
- 61/548 . . . {using radioactive means to promote ionisation}
- 61/56 . . One or more circuit elements structurally associated with the lamp
- 61/58 . Lamps with both liquid anode and liquid cathode
- 61/60 . Lamps in which the discharge space is substantially filled with mercury before ignition
- 61/62 . Lamps with gaseous cathode, e.g. plasma cathode
- 61/64 . Cathode glow lamps
- 61/66 . . having one or more specially shaped cathodes, e.g. for advertising purposes {alphanumeric}
- 61/68 . Lamps in which the main discharge is between parts of a current-carrying guide, e.g. halo lamp
- 61/70 . Lamps with low-pressure unstricted discharge {having a cold pressure < 400 Torr}
- 61/72 . . having a main light-emitting filling of easily vaporisable metal vapour, e.g. mercury
- 61/74 . . having a main light-emitting filling of difficult vaporisable metal vapour, e.g. sodium
- 61/76 . . having a filling of permanent gas or gases only
- 61/78 . . . with cold cathode; with cathode heated only by discharge, e.g. high-tension lamp for advertising
- 61/80 . . Lamps suitable only for intermittent operation, e.g. flash lamp
- 61/82 . Lamps with high-pressure unstricted discharge {having a cold pressure > 400 Torr}
- 61/822 . . {High-pressure mercury lamps}
- 61/825 . . {High-pressure sodium lamps}
- 61/827 . . {Metal halide arc lamps}
- 61/84 . Lamps with discharge constricted by high pressure

61/86	. . with discharge additionally constricted by close spacing of electrodes, e.g. for optical projection	2201/2814 being a mesh-like network
61/88	. . with discharge additionally constricted by envelope	2201/2817	. . . Rods
61/90	. . Lamps suitable only for intermittent operation, e.g. flash lamp	2201/2821	. . . Envelope or cross-section
61/92	. Lamps with more than one main discharge path	2201/2825 being oval or elliptic
61/94	. . Paths producing light of different wavelengths, e.g. for simulating daylight	2201/2828 being rectangular or square
61/95	. Lamps with control electrode for varying intensity or wavelength of the light, e.g. for producing modulated light	2201/2832 being circular
61/96	. Lamps with light-emitting discharge path and separately-heated incandescent body within a common envelope, e.g. for simulating daylight	2201/2835	. . . Folded
61/98	. Lamps with closely spaced electrodes heated to incandescence by light-emitting discharge, e.g. tungsten arc lamp	2201/2839 Hair-pin or simple bend
63/00	Cathode-ray or electron-stream lamps	2201/2842	. . . Conic
63/02	. Details, e.g. electrode, gas filling, shape of vessel	2201/2846	. . . Loop
63/04	. . Vessels provided with luminescent coatings; Selection of materials for the coatings	2201/285	. . . Plurality of elements
63/06	. Lamps with luminescent screen excited by the ray or stream	2201/2853	. . . Serpentine
63/08	. Lamps with gas plasma excited by the ray or stream	2201/2857 being coiled
65/00	Lamps without any electrode inside the vessel; Lamps with at least one main electrode outside the vessel	2201/286 being looped
65/04	. Lamps in which a gas filling is excited to luminesce by an external electromagnetic field or by external corpuscular radiation, e.g. for indicating { plasma display panels }	2201/2864	. . . Ribbon or bar
65/042	. . { by an external electromagnetic field }	2201/2867	. . . Spiral or helix
65/044	. . . { the field being produced by a separate microwave unit }	2201/2871 being flattened
65/046	. . . { the field being produced by using capacitive means around the vessel }	2201/2875 being double, reverse helix or interwoven
65/048	. . . { the field being produced by using an excitation coil }	2201/2878	. . . Thin film or film-like
65/06	. Lamps in which a gas filling is excited to luminesce by radioactive material structurally associated with the lamp, e.g. inside the vessel	2201/2882	. . . Variable winding density
65/08	. Lamps in which a screen or coating is excited to luminesce by radioactive material located inside the vessel { (direct conversion of radiation energy from radioactive sources into light G21H 3/02) }	2201/2885	. . . Twisted
99/00	Subject matter not provided for in other groups of this subclass	2201/2889	. . Characterised by material
2201/00	Electrodes common to discharge tubes	2201/2892	. . Coatings
2201/02	. Arrangements for eliminating deleterious effects	2201/2896	. . . Insulating layers
2201/025	. . charging	2201/30	. Cold cathodes
2201/19	. Thermionic cathodes	2201/304	. . Field emission cathodes
2201/193	. . Thin film cathodes	2201/30403	. . . characterised by the emitter shape
2201/196	. . Emission assisted by other physical processes, e.g. field- or photo emission	2201/30407 Microengineered point emitters
2201/28	. Heaters for thermionic cathodes	2201/30411 conical shaped, e.g. Spindt type
2201/2803	. . Characterised by the shape or size	2201/30415 needle shaped
2201/2807	. . . Block	2201/30419 Pillar shaped emitters
2201/281	. . . Cage-like construction	2201/30423 Microengineered edge emitters
		2201/30426 Coatings on the emitter surface, e.g. with low work function materials
		2201/3043 Fibres
		2201/30434 Nanotubes
		2201/30438 Particles
		2201/30442 Whiskers
		2201/30446	. . . characterised by the emitter material
		2201/30449 Metals and metal alloys
		2201/30453 Carbon types
		2201/30457 Diamond
		2201/30461 Graphite
		2201/30465 Fullerenes
		2201/30469 Carbon nanotubes (CNTs)
		2201/30473 Amorphous carbon
		2201/30476 Diamond-like carbon [DLC]
		2201/3048 Semiconductor materials
		2201/30484 Carbides
		2201/30488 Nitrides
		2201/30492 Borides
		2201/30496 Oxides
		2201/306	. . Ferroelectric cathodes
		2201/308	. . Semiconductor cathodes, e.g. having PN junction layers
		2201/312	. . having an electric field perpendicular to the surface thereof
		2201/3125	. . . Metal-insulator-Metal [MIM] emission type cathodes
		2201/316	. . having an electric field parallel to the surface thereof, e.g. thin film cathodes
		2201/3165	. . . Surface conduction emission type cathodes

- 2201/317 . . combined with other synergetic effects, e.g. secondary, photo- or thermal emission
- 2201/319 . . Circuit elements associated with the emitters by direct integration
- 2201/3195 . . . Resistive members, e.g. resistive layers
- 2201/32 . . Secondary emission electrodes
- 2201/34 . . Photoemissive electrodes
- 2201/342 . . Cathodes
- 2201/3421 . . . Composition of the emitting surface
- 2201/3423 Semiconductors, e.g. GaAs, NEA emitters
- 2201/3425 Metals, metal alloys
- 2201/3426 Alkaline metal compounds, e.g. Na-K-Sb
- 2201/3428 Organo-metallic compounds, e.g. Ferrocene
- 2203/00 Electron or ion optical arrangements common to discharge tubes or lamps**
- 2203/02 . Electron guns
- 2203/0204 . . using cold cathodes, e.g. field emission cathodes
- 2203/0208 . . . Control electrodes
- 2203/0212 Gate electrodes
- 2203/0216 characterised by the form or structure
- 2203/022 Shapes or dimensions of gate openings
- 2203/0224 Arrangement of gate openings
- 2203/0228 Curved/extending upwardly
- 2203/0232 characterised by the material
- 2203/0236 Relative position to the emitters, cathodes or substrates
- 2203/024 Focusing electrodes
- 2203/0244 characterised by the form or structure
- 2203/0248 Shapes or dimensions of focusing electrode openings
- 2203/0252 Arrangement of focusing electrode openings
- 2203/0256 characterised by the material
- 2203/026 Relative position to the gateelectrodes, emitters, cathodes or substrates
- 2203/0264 In the same plane as the gate electrodes or cathodes
- 2203/0268 . . . Insulation layer
- 2203/0272 for gate electrodes
- 2203/0276 for focusing electrodes
- 2203/028 characterised by the shape
- 2203/0284 Dimensions of openings
- 2203/0288 characterised by the material
- 2203/0292 . . . Potentials applied to the electrodes
- 2203/0296 . . Spin-polarised beams
- 2203/04 . Ion guns
- 2209/00 Apparatus and processes for manufacture of discharge tubes**
- 2209/01 . Generalised techniques
- 2209/012 . . Coating
- 2209/015 . . . Machines therefor
- 2209/017 . . Cleaning
- 2209/02 . Manufacture of cathodes
- 2209/022 . . Cold cathodes
- 2209/0223 . . . Field emission cathodes
- 2209/0226 Sharpening or resharpening of emitting point or edge
- 2209/18 . Assembling together the component parts of the discharge tube
- 2209/185 . . Machines therefor, e.g. electron gun assembling devices
- 2209/236 . . Manufacture of magnetic deflecting devices
- 2209/2363 . . Coils
- 2209/2366 . . . Machines therefor, e.g. winding, forming, welding, or the like
- 2209/26 . Sealing parts of the vessel to provide a vacuum enclosure
- 2209/261 . . Apparatus used for sealing vessels, e.g. furnaces, machines or the like
- 2209/262 . . . means for applying sealing materials, e.g. frit paste dispensers
- 2209/264 . . Materials for sealing vessels, e.g. frit glass compounds, resins or structures
- 2209/265 . . Surfaces for sealing vessels
- 2209/267 . . . shaped surfaces or flanges
- 2209/268 . . . treated surfaces and surface preparations, e.g. to improve adhesion
- 2209/38 . Control of maintenance of pressure in the vessel
- 2209/383 . . Vacuum pumps
- 2209/385 . . Gettering
- 2209/3855 . . . Getter materials
- 2209/387 . . Gas filling
- 2209/389 . . Degassing
- 2209/3893 . . . by a discharge
- 2209/3896 . . . by heating
- 2209/46 . Handling of tube components during manufacture
- 2209/463 . . Identifying or selecting component pieces
- 2209/466 . . . Marking, e.g. bar-codes
- 2211/00 Plasma display panels with alternate current induction of the discharge, e.g. AC-PDPs**
- 2211/10 . AC-PDPs with at least one main electrode being out of contact with the plasma
- 2211/12 . . with main electrodes provided on both sides of the discharge space
- 2211/14 . . with main electrodes provided only on one side of the discharge space
- 2211/16 . . with main electrodes provided inside or on the side face of the spacers
- 2211/18 . . containing a plurality of independent closed structures for containing the gas, e.g. plasma tube array [PTA] display panels
- 2211/20 . Constructional details
- 2211/22 . . Electrodes
- 2211/225 . . . Material of electrodes
- 2211/24 . . . Sustain electrodes or scan electrodes
- 2211/245 Shape, e.g. cross section or pattern
- 2211/26 . . . Address electrodes
- 2211/265 Shape, e.g. cross section or pattern
- 2211/28 . . . Auxiliary electrodes, e.g. priming electrodes or trigger electrodes
- 2211/30 . . . Floating electrodes
- 2211/32 . . . Disposition of the electrodes
- 2211/323 Mutual disposition of electrodes
- 2211/326 Disposition of electrodes with respect to cell parameters ([H01J 2211/323 takes precedence](#)), e.g. electrodes within the ribs
- 2211/34 . . Vessels, containers or parts thereof, e.g. substrates
- 2211/36 . . . Spacers, barriers, ribs, partitions or the like
- 2211/361 characterized by the shape
- 2211/363 Cross section of the spacers
- 2211/365 Pattern of the spacers
- 2211/366 characterized by the material

2211/368 Dummy spacers, e.g. in a non display region	2223/00	Details of transit-time tubes of the types covered by group H01J 2225/00
2211/38	. . . Dielectric or insulating layers	2223/005	. Cooling methods or arrangements
2211/40	. . . Layers for protecting or enhancing the electron emission, e.g. MgO layers	2223/02	. Electrodes; Magnetic control means; Screens
2211/42	. . . Fluorescent layers	2223/027	. . Collectors
2211/44	. . . Optical arrangements or shielding arrangements, e.g. filters or lenses	2223/0275	. . . Multistage collectors
2211/442 Light reflecting means; Anti-reflection means	2223/033	. . . Collector cooling devices
2211/444 Means for improving contrast or colour purity, e.g. black matrix or light shielding means	2223/04	. . Cathodes
2211/446 Electromagnetic shielding means; Antistatic means	2223/05	. . . having a cylindrical emissive surface, e.g. cathodes for magnetrons
2211/448 Near infrared shielding means	2223/06	. . Electron or ion guns
2211/46	. . Connecting or feeding means, e.g. leading-in conductors	2223/065	. . . producing a solid cylindrical beam
2211/48	. . Sealing, e.g. seals specially adapted for leading-in conductors	2223/07	. . . producing a hollow cylindrical beam
2211/50	. . Filling, e.g. selection of gas mixture	2223/075	. . . Magnetron injection guns
2211/52	. . Means for absorbing or adsorbing the gas mixture, e.g. by gettering	2223/08	. . Focusing arrangements, e.g. for concentrating stream of electrons, for preventing spreading of stream
2211/54	. . Means for exhausting the gas	2223/083	. . . Electrostatic focusing arrangements
2211/62	. . Circuit arrangements	2223/087	. . . Magnetic focusing arrangements
2211/66	. . Cooling arrangements	2223/0873 with at least one axial- field reversal along the interaction space, e.g. P.P.M. focusing
2217/00	Gas-filled discharge tubes	2223/0876 with arrangements improving the linearity and homogeneity of the axial field, e.g. field straightener
2217/04	. Electrodes	2223/09	. . Electric system for directing or deflecting the discharge along a desired path, e.g. E-type
2217/06	. . Cathodes	2223/10	. . Magnet systems for directing or deflecting the discharge along a desired path, e.g. a spiral path
2217/062	. . . thermionic	2223/11	. . Means for reducing noise
2217/065	. . . heated by the discharge	2223/12	. Vessels; Containers
2217/067	. . . Cold cathodes	2223/14	. Leading-in arrangements; Seals therefor
2217/10	. . Anodes	2223/15	. . Means for preventing wave energy leakage structurally associated with tube leading-in arrangements, e.g. filters, chokes, attenuating devices
2217/12	. . Control electrodes	2223/16	. Circuit elements, having distributed capacitance and inductance, structurally associated with the tube and interacting with the discharge
2217/38	. Cold-cathode tubes	2223/165	. . Manufacturing processes or apparatus therefore
2217/40	. . Gas discharge switches	2223/18	. . Resonators
2217/402	. . . Multiple switches	2223/20	. . . Cavity resonators; Adjustment or tuning thereof
2217/4025 for addressing electro-optical devices, i.e. LCD's	2223/207 Tuning of single resonator
2217/49	. . Display panels, e.g. not making use of alternating current (H01J 2211/10 takes precedence)	2223/213 Simultaneous tuning of more than one resonator, e.g. resonant cavities of a magnetron
2217/491	. . . characterised by problems peculiar to plasma displays	2223/22	. . . Connections between resonators, e.g. strapping for connecting resonators of a magnetron
2217/4915 Luminosity	2223/24	. . Slow-wave structures, e.g. delay systems
2217/492	. . . Details	2223/26	. . . Helical slow-wave structures; Adjustment therefor
2217/49207 Electrodes	2223/27 Helix-derived slow-wave structures
2217/49214 Shape	2223/28	. . . Interdigital slow-wave structures; Adjustment therefor
2217/49221 Mutual disposition	2223/30	. . . Damping arrangements associated with slow-wave structures, e.g. for suppression of unwanted oscillations
2217/49228 Crossed electrodes	2223/34	. Circuit arrangements not adapted to a particular application of the tube and not otherwise provided for
2217/49235 Side-by-side electrodes	2223/36	. Coupling devices having distributed capacitance and inductance, structurally associated with the tube, for introducing or removing wave energy
2217/49242 Auxiliary electrodes	2223/38	. . to or from the discharge
2217/4925 Mounting, supporting, spacing		
2217/49257 Means for isolating electrodes from the discharge, e.g. dielectric layers		
2217/49264 Vessels		
2217/49271 Spacers between front and back panels		
2217/49278 Coatings (H01J 2217/49292 takes precedence)		
2217/49285 Associated optical means		
2217/49292 Filters		
2217/494	. . . A.C. panels		
2217/498	. . . Hybrid panels (AC and DC)		

- 2223/40 . . . to or from the interaction circuit
- 2223/42 . . . the interaction circuit being a helix or a helix-derived slow-wave structure
- 2223/44 . . . Rod-type coupling devices
- 2223/46 . . . Loop coupling devices
- 2223/48 . . . for linking interaction circuit with coaxial lines; Devices of the coupled helices type
- 2223/50 the interaction circuit being a helix or derived from a helix
- 2223/52 the coupled helices being disposed coaxially around one another
- 2223/54 . . Filtering devices preventing unwanted frequencies or modes to be coupled to, or out of, the interaction circuit; Prevention of high frequency leakage in the environment
- 2225/00 Transit-time tubes, e.g. Klystrons, travelling-wave tubes, magnetrons**
- 2225/005 . Gas-filled transit-time tubes
- 2225/02 . Tubes with electron stream modulated in velocity or density in a modulator zone and thereafter giving up energy in an inducing zone, the zones being associated with one or more resonators
- 2225/025 . . with an electron stream following a helical path
- 2225/04 . . Tubes having one or more resonators, without reflection of the electron stream, and in which the modulation produced in the modulator zone is mainly density modulation, e.g. Heaff tube
- 2225/06 . . Tubes having only one resonator, without reflection of the electron stream, and in which the modulation produced in the modulator zone is mainly velocity modulation, e.g. Lüdi-Klystron
- 2225/08 . . . with electron stream perpendicular to the axis of the resonator
- 2225/10 . . Klystrons, i.e. tubes having two or more resonators, without reflection of the electron stream, and in which the stream is modulated mainly by velocity in the zone of the input resonator
- 2225/11 . . . Extended interaction Klystrons
- 2225/12 . . . with pencil-like electron stream in the axis of the resonators
- 2225/14 . . . with tube-like electron stream coaxial with the axis of the resonators
- 2225/16 . . . with pencil-like electron stream perpendicular to the axis of the resonators
- 2225/18 . . . with radial or disc-like electron stream perpendicular to the axis of the resonators
- 2225/20 . . . having special arrangements in the space between resonators, e.g. resistive-wall amplifier tube, space-charge amplifier tube, velocity-jump tube
- 2225/22 . . Reflex Klystrons, i.e. tubes having one or more resonators, with a single reflection of the electron stream, and in which the stream is modulated mainly by velocity in the modulator zone
- 2225/24 . . . in which the electron stream is in the axis of the resonator or resonators and is pencil-like before reflection
- 2225/26 . . . in which the electron stream is coaxial with the axis of the resonator or resonators and is tube-like before reflection
- 2225/28 . . . in which the electron stream is perpendicular to the axis of the resonator or resonators and is pencil-like before reflection
- 2225/30 . . . in which the electron stream is perpendicular to the axis of the resonator or resonators and is radial or disc-like before reflection
- 2225/32 . . Tubes with plural reflection, e.g. Coeterier tube
- 2225/34 . Travelling-wave tubes; Tubes in which a travelling wave is simulated at spaced gaps
- 2225/36 . . Tubes in which an electron stream interacts with a wave travelling along a delay line or equivalent sequence of impedance elements, and without magnet system producing an H-field crossing the E-field
- 2225/38 . . . the forward travelling wave being utilised
- 2225/40 . . . the backward travelling wave being utilised
- 2225/42 . . Tubes in which an electron stream interacts with a wave travelling along a delay line or equivalent sequence of impedance elements, and with a magnet system producing an H-field crossing the E-field
- 2225/44 . . . the forward travelling wave being utilised
- 2225/46 . . . the backward travelling wave being utilised
- 2225/48 . . Tubes in which two electron streams of different velocities interact with one another, e.g. electron-wave tube
- 2225/49 . . Tubes using the parametric principle, e.g. for parametric amplification
- 2225/50 . Magnetrons, i.e. tubes with a magnet system producing an H-field crossing the E-field
- 2225/52 . . with an electron space having a shape that does not prevent any electron from moving completely around the cathode or guide electrode
- 2225/54 . . . having only one cavity or other resonator, e.g. neutrode tube
- 2225/55 Coaxial cavity magnetrons
- 2225/56 with interdigital arrangements of anodes, e.g. turbator tube
- 2225/58 . . . having a number of resonators; having a composite resonator, e.g. a helix
- 2225/587 Multi-cavity magnetrons
- 2225/593 Rising-sun magnetrons
- 2225/60 . . with an electron space having a shape that prevents any electron from moving completely around the cathode or guide electrode; Linear magnetrons
- 2225/61 . Hybrid tubes, i.e. tubes comprising a klystron section and a travelling-wave section
- 2225/62 . Strophotrons, i.e. tubes with H-field crossing the E-field and functioning with plural reflection
- 2225/64 . Turbine tubes, i.e. tubes with H-field crossing the E-field and functioning with reversed cyclotron action
- 2225/66 . Tubes with electron stream crossing itself and thereby interacting or interfering with itself
- 2225/68 . Tubes specially designed to act as oscillator with positive grid and retarding field, e.g. for Barkhausen-Kurz oscillators
- 2225/70 . . with resonator having distributed inductance with capacitance, e.g. Pintsch tube
- 2225/72 . . in which a standing wave or a considerable part thereof is produced along an electrode, e.g. Clavier tube
- 2225/74 . Tubes specially designed to act as transit-time diode oscillators, e.g. monotron
- 2225/76 . Dynamic electron-multiplier tubes, e.g. Farnsworth multiplier tube, multipactor

2225/78	. Tubes with electron stream modulated by deflection in a resonator	2229/4844	. characterised by beam passing apertures or combinations
2229/00	Details of cathode ray tubes or electron beam tubes (H01J 2329/00 takes precedence)	2229/4848	. . . Aperture shape as viewed along beam axis
2229/0007	. Elimination of unwanted or stray electromagnetic effects	2229/4851 trapezoidal
2229/0015	. . Preventing or cancelling fields leaving the enclosure	2229/4855 with rounded end or ends
2229/0023	. . . Passive means	2229/4858 parallelogram
2229/003	. . Preventing or cancelling fields entering the enclosure	2229/4862 square
2229/0038	. . . Active means	2229/4865 rectangle
2229/0046	. . Preventing or cancelling fields within the enclosure	2229/4868 with rounded end or ends
2229/0053	. . . Demagnetisation	2229/4872 circular
2229/0061	. Cooling arrangements	2229/4875 oval
2229/0069	. . Active means, e.g. fluid flow	2229/4879 non-symmetric about field scanning axis
2229/0076	. . . applied to the faceplate	2229/4882 non-symmetric about line scanning axis
2229/0084 Translucent coolant, e.g. flowing across faceplate	2229/4886 polygonal
2229/0092	. . Passive means, e.g. fins, heat conductors	2229/4889 cross shaped
2229/07	. Shadow masks	2229/4893 Interconnected apertures
2229/0705	. . Mounting arrangement of assembly to vessel	2229/4896 complex and not provided for
2229/0711	. . . Spring and plate (clip) type	2229/50	. . Plurality of guns or beams
2229/0716	. . Mounting arrangements of aperture plate to frame or vessel	2229/502	. . . Three beam guns, e.g. for colour CRTs
2229/0722	. . Frame	2229/505	. . . Arrays
2229/0727	. . Aperture plate	2229/507	. . . Multi-beam groups, e.g. number of beams greater than number of cathodes
2229/0733	. . . characterised by the material	2229/56	. Correction of beam optics
2229/0738	. . . Mitigating undesirable mechanical effects	2229/563	. . Aberrations by type
2229/0744 Vibrations	2229/5632	. . . Spherical
2229/075	. . . Beam passing apertures, e.g. geometrical arrangements	2229/5635	. . . Astigmatism
2229/0755 characterised by aperture shape	2229/5637	. . . Colour purity
2229/0761 Uniaxial masks having parallel slit apertures, i.e. Trinitron type	2229/568	. . using supplementary correction devices
2229/0766	. . . Details of skirt or border	2229/5681	. . . magnetic
2229/0772 Apertures, cut-outs, depressions, or the like	2229/5682 Permanently magnetised materials, e.g. permanent magnets
2229/0777	. . . Coatings	2229/5684 Magnetic materials, e.g. soft iron
2229/0783 improving thermal radiation properties	2229/5685 Cross-arms field shaper
2229/0788 Parameterised dimensions of aperture plate, e.g. relationships, polynomial expressions	2229/5687 Auxiliary coils
2229/0794	. . Geometrical arrangements, e.g. curvature	2229/5688 Velocity modulation
2229/18	. Phosphor screens	2229/58	. Electron beam control inside the vessel
2229/183	. . multi-layer	2229/581	. . by magnetic means
2229/186	. . Geometrical arrangement of phosphors	2229/582	. . by electrostatic means
2229/48	. Electron guns	2229/583	. . at the source
2229/4803	. . Electrodes	2229/5835	. . . cooperating with the electron gun
2229/4806	. . . Shield centering cups	2229/585	. . at the screen
2229/481	. . . Focusing electrodes	2229/587	. . between the source and the screen
2229/4813 Pre-focusing	2229/70	. Electron beam control outside the vessel
2229/4817 Accelerating electrodes	2229/703	. . by magnetic fields
2229/482	. . . Extraction grids	2229/7031	. . . Cores for field producing elements, e.g. ferrite
2229/4824	. . Constructional arrangements of electrodes	2229/7032	. . . Conductor design and distribution
2229/4827	. . . Electrodes formed on surface of common cylindrical support	2229/7033 Winding
2229/4831	. . . Electrode supports	2229/7035 Wires and conductors
2229/4834	. . Electrical arrangements coupled to electrodes, e.g. potentials	2229/7036 Form of conductor
2229/4837	. . . characterised by the potentials applied	2229/7037 flat, e.g. foil, or ribbon type
2229/4841 Dynamic potentials	2229/7038 Coil separators and formers
		2229/86	. Vessels and containers
		2229/8603	. . Neck or cone portions of the CRT vessel
		2229/8606	. . . characterised by the shape
		2229/8609 Non circular cross-sections
		2229/8613	. . Faceplates
		2229/8616	. . . characterised by shape
		2229/862 Parameterised shape, e.g. expression, relationship or equation
		2229/8623	. . Substrates
		2229/8626	. . Frames
		2229/863	. Passive shielding means associated with the vessel

2229/8631	. . Coatings	2231/123	. . . by direct current detection, e.g. collecting electrodes
2229/8632	. . . characterised by the material	2231/125	. . with a plurality of electron guns within the tube envelope
2229/8633	. . Meshes and patterns	2231/1255	. . . two or more neck portions containing one or more guns
2229/8634	. . Magnetic shielding	2231/50	. Imaging and conversion tubes
2229/8635	. . Antistatic shielding	2231/50005	. . characterised by form of illumination
2229/8636	. . Electromagnetic shielding	2231/5001	. . . Photons
2229/8637	. . Mechanical shielding, e.g. against water or abrasion	2231/50015 Light
2229/8638	. . Ionising radiation shielding, e.g. X-rays	2231/50021 Ultraviolet
2229/87	. Means for avoiding vessel implosion	2231/50026 Infrared
2229/875	. . Means substantially covering the output face, e.g. resin layers, protective panels	2231/50031 High energy photons
2229/88	. Coatings	2231/50036 X-rays
2229/882	. . having particular electrical resistive or conductive properties	2231/50042	. . . Particles
2229/885	. . having particular electrical insulation properties	2231/50047 Charged particles
2229/887	. . having particular X-ray shielding properties	2231/50052	. . . Mechanical vibrations, e.g. sound
2229/89	. Optical components associated with the vessel	2231/50057	. . characterised by form of output stage
2229/8901	. . Fixing of optical components to the vessel	2231/50063	. . . Optical
2229/8903	. . Fibre optic components	2231/50068	. . . Electrical
2229/8905	. . Direction sensitive devices for controlled viewing angle	2231/50073 Charge coupled device [CCD]
2229/8907	. . Image projection devices	2231/50078 Resistive anode
2229/8909	. . Baffles, shutters, apertures or the like against external light	2231/50084 using light or electron beam scanning
2229/8911	. . . Large-scale devices, e.g. foldable screens	2231/50089	. . . Having optical stage before electrical conversion
2229/8913	. . Anti-reflection, anti-glare, viewing angle and contrast improving treatments or devices	2231/50094 Charge coupled device [CCD]
2229/8915	. . . Surface treatment of vessel or device, e.g. controlled surface roughness	2231/501	. . including multiplication stage
2229/8916	. . . inside the vessel	2231/5013	. . . with secondary emission electrodes
2229/8918	. . . by using interference effects	2231/5016 Microchannel plates [MCP]
2229/892	. . . Effect varying over surface	2231/503	. . with scanning or gating optics
2229/8922	. . . Apparatus attached to vessel and not integral therewith	2231/5033	. . . electrostatic
2229/8924	. . having particular properties for protecting the vessel, e.g. against abrasion, water or shock	2231/5036	. . . magnetic
2229/8926	. . Active components, e.g. LCD's, indicators, illuminators and moving devices	2231/505	. . with non-scanning optics
2229/8928	. . Laser CRTs	2231/5053	. . . electrostatic
2229/893	. . using lenses	2231/5056	. . . magnetic
2229/899	. . Photographic devices (permanent recording of images)	2235/00	X-ray tubes
2229/92	. Means providing or assisting electrical connection with or within the tube	2235/02	. Electrical arrangements
2229/922	. . within the tube	2235/023	. . Connecting of signals or tensions to or through the vessel
2229/925	. . associated with the high tension [HT], e.g. anode potentials	2235/0233	. . . High tension
2229/927	. . associated with digital scanning	2235/0236	. . . Indirect coupling, e.g. capacitive or inductive
2229/94	. Means for obtaining or maintaining the desired pressure within the tube	2235/06	. Cathode assembly
2229/96	. Circuit elements other than coils, reactors or the like, associated with the tube	2235/062	. . Cold cathodes
2229/962	. . associated with the HT	2235/064	. . Movement of cathode
2229/964	. . associated with the deflection system	2235/066	. . . Rotation
2229/966	. . associated with the gun structure	2235/068	. . Multi-cathode assembly
2229/968	. . . Resistors	2235/08	. Targets (anodes) and X-ray converters
2231/00	Cathode ray tubes or electron beam tubes (H01J 2329/00 takes precedence)	2235/081	. . Target material
2231/12	. CRTs having luminescent screens	2235/082	. . . Fluids, e.g. liquids, gases
2231/121	. . Means for indicating the position of the beam, e.g. beam indexing	2235/083	. . Bonding or fixing with the support or substrate
		2235/084	. . . Target-substrate interlayers or structures, e.g. to control or prevent diffusion or improve adhesion
		2235/085	. . Target treatment, e.g. ageing, heating
		2235/086	. . Target geometry
		2235/088	. . Laminated targets, e.g. plurality of emitting layers of unique or differing materials
		2235/10	. Drive means for anode (target) substrate
		2235/1006	. . Supports or shafts for target or substrate
		2235/1013	. . . Fixing to the target or substrate
		2235/102	. . . Materials for the shaft

2235/1026	. . Means (motors) for driving the target (anode)	2. Same rules apply for manufacturing procedures (H01J 2209/00), unless really specific to the tube concerned.
2235/1033	. . . mounted within the vacuum vessel	3. The codes in this main group are grouped according to the following principle:
2235/104	. . . characterised by the shape	details common to gas or plasma discharge of the above mentioned tubes:
2235/1046	. . Bearings and bearing contact surfaces	H01J 2237/00 - H01J 2237/2487
2235/1053	. . . Retainers or races	Imaging or analysing:
2235/106	. . . Dynamic pressure bearings, e.g. helical groove type	H01J 2237/25 - H01J 2237/2857
2235/1066	. . . Treated contact surfaces, e.g. coatings	particle beam processing:
2235/1073	. . . Magnetic bearings	H01J 2237/30 - H01J 2237/31798
2235/108	. . Lubricants	plasma processing:
2235/1086	. . . liquid metals	H01J 2237/32 - H01J 2237/339
2235/1093	. . Measures for preventing vibration	
2235/12	. Cooling	
2235/1204	. . of the anode	2237/002 . Cooling arrangements
2235/1208	. . of the bearing assembly	2237/004 . Charge control of objects or beams
2235/1212	. . of the cathode	2237/0041 . . Neutralising arrangements
2235/1216	. . of the vessel	2237/0042 . . . Deflection of neutralising particles
2235/122	. . of the window	2237/0044 . . . of objects being observed or treated
2235/1225	. . characterised by method	2237/0045 using secondary electrons
2235/1229	. . . employing layers with high emissivity	2237/0047 using electromagnetic radiations, e.g. UV, X-rays, light
2235/1233 characterised by the material	2237/0048 . . Charging arrangements
2235/1237 Oxides	2237/006 . Details of gas supplies, e.g. in an ion source, to a beam line, to a specimen or to a workpiece, (H01J 37/3244 takes precedence; environmental cells for electron microscopes H01J 2237/2003 ; microscopes with environmental specimen chamber H01J 2237/2608)
2235/1241 Bonding layer to substrate	2237/02 . Details
2235/1245	. . . Increasing emissive surface area	2237/0203 . . Protection arrangements
2235/125 with interdigitated fins or slots	2237/0206 . . . Extinguishing, preventing or controlling unwanted discharges
2235/1254 with microscopic surface features	2237/0209 . . . Avoiding or diminishing effects of eddy currents
2235/1258	. . . Placing objects in close proximity	2237/0213 . . . Avoiding deleterious effects due to interactions between particles and tube elements
2235/1262	. . . Circulating fluids	2237/0216 . . Means for avoiding or correcting vibration effects
2235/1266 flow being via moving conduit or shaft	2237/022 . . Avoiding or removing foreign or contaminating particles, debris or deposits on sample or tube
2235/127 Control of flow	2237/0225 . . . Detecting or monitoring foreign particles
2235/1275 characterised by the fluid	2237/024 . . Moving components not otherwise provided for
2235/1279 Liquid metals	2237/0245 . . . Moving whole optical system relatively to object
2235/1283 in conjunction with extended surfaces (e.g. fins or ridges)	2237/026 . . Shields
2235/1287 Heat pipes	2237/0262 . . . electrostatic
2235/1291	. . . Thermal conductivity	2237/0264 . . . magnetic
2235/1295 Contact between conducting bodies	2237/0266 . . . electromagnetic
2235/16	. Vessels	2237/0268 . . . Liner tubes
2235/161	. . Non-stationary vessels	2237/028 . . Particle traps
2235/162	. . . Rotation	2237/03 . Mounting, supporting, spacing or insulating electrodes
2235/163	. . shaped for a particular application	2237/032 . . Mounting or supporting
2235/164	. . . Small cross-section, e.g. for entering in a body cavity	2237/036 . . Spacing
2235/165	. . Shielding arrangements	2237/038 . . Insulating
2235/166	. . . against electromagnetic radiation	2237/04 . Means for controlling the discharge
2235/167	. . . against thermal (heat) energy	2237/041 . . Beam polarising means
2235/168	. . . against charged particles	2237/043 . . Beam blanking
2235/18	. Windows, e.g. for X-ray transmission	2237/0432 . . . High speed and short duration
2235/183	. . Multi-layer structures	2237/0435 . . . Multi-aperture
2235/20	. Arrangements for controlling gases within the X-ray tube	2237/0437 Semiconductor substrate
2235/205	. . Gettering	2237/045 . . Diaphragms
2237/00	Discharge tubes exposing object to beam, e.g. for analysis treatment, etching, imaging	2237/0451 . . . with fixed aperture
NOTES		
1. For features of general interest which may be found in other types of discharge tubes, an indexing code corresponding to general schemes H01J 2201/00 - H01J 2203/00 is given, e.g. for cathodes, vessels, cooling means or the like		

2237/0453 multiple apertures	2237/1205 Microlenses
2237/0455 with variable aperture	2237/1207 Einzel lenses
2237/0456 Supports	2237/121 characterised by shape
2237/0458 movable, i.e. for changing between differently sized apertures	2237/1215 Annular electrodes
2237/047	. . . Changing particle velocity	2237/14	. . . magnetic
2237/0473 accelerating	2237/1405 Constructional details
2237/04732 with magnetic means	2237/141 Coils
2237/04735 with electrostatic means	2237/1415 Bores or yokes, i.e. magnetic circuit in general
2237/04737 radio-frequency quadrupole [RFQ]	2237/142 with superconducting coils
2237/0475 decelerating	2237/15	. . Means for deflecting or directing discharge
2237/04753 with magnetic means	2237/1501	. . Beam alignment means or procedures
2237/04756 with electrostatic means	2237/1502	. . Mechanical adjustments
2237/049	. . Focusing means	2237/1503	. . . Mechanical scanning
2237/0492	. . . Lens systems	2237/1504	. . Associated circuits
2237/04922 electromagnetic	2237/1505	. . Rotating beam around optical axis
2237/04924 electrostatic	2237/1506	. . Tilting or rocking beam around an axis substantially at an angle to optical axis
2237/04926 combined	2237/1507	. . . dynamically, e.g. to obtain same impinging angle on whole area
2237/04928 Telecentric systems	2237/1508	. . Combined electrostatic-electromagnetic means
2237/05	. Arrangements for energy or mass analysis	2237/151	. . Electrostatic means
2237/053	. . electrostatic	2237/1512	. . . Travelling wave deflectors
2237/0535	. . . Mirror analyser	2237/1514	. . . Prisms
2237/055	. . magnetic	2237/1516	. . . Multipoles
2237/057	. . Energy or mass filtering	2237/1518	. . . for X-Y scanning
2237/06	. Sources	2237/152	. . Magnetic means
2237/061	. . Construction	2237/1523	. . . Prisms
2237/062	. . . Reducing size of gun	2237/1526	. . . For X-Y scanning
2237/063	. . Electron sources	2237/153	. . Correcting image defects, e.g. stigmators
2237/06308	. . . Thermionic sources	2237/1532	. . Astigmatism
2237/06316 Schottky emission	2237/1534	. . Aberrations
2237/06325	. . . Cold-cathode sources	2237/1536	. . Image distortions due to scanning
2237/06333 Photo emission	2237/1538	. . Space charge (Boersch) effect compensation
2237/06341 Field emission	2237/16	. Vessels
2237/0635 Multiple source, e.g. comb or array	2237/162	. . Open vessel, i.e. one end sealed by object or workpiece
2237/06358 Secondary emission	2237/164	. . Particle-permeable windows
2237/06366 Gas discharge electron sources	2237/166	. . Sealing means
2237/06375	. . . Arrangement of electrodes	2237/18	. Vacuum control means
2237/06383	. . . Spin polarised electron sources	2237/182	. . Obtaining or maintaining desired pressure
2237/06391	. . . Positron sources	2237/1825	. . . Evacuating means
2237/065	. . Source emittance characteristics	2237/184	. . Vacuum locks
2237/0653	. . . Intensity	2237/186	. . Valves
2237/0656	. . . Density	2237/188	. . Differential pressure
2237/08	. . Ion sources	2237/20	. Positioning, supporting, modifying or maintaining the physical state of objects being observed or treated
2237/0802	. . . Field ionization sources	2237/2001	. . Maintaining constant desired temperature
2237/0805 Liquid metal sources	2237/2002	. . Controlling environment of sample
2237/0807 Gas field ion sources [GFIS]	2237/2003	. . . Environmental cells
2237/081	. . . Sputtering sources	2237/2004 Biological samples
2237/0812	. . . Ionized cluster beam [ICB] sources	2237/2005	. . Seal mechanisms
2237/0815	. . . Methods of ionisation	2237/2006	. . . Vacuum seals
2237/0817 Microwaves	2237/2007	. . Holding mechanisms
2237/082 Electron beam	2237/2008	. . specially adapted for studying electrical or magnetical properties of objects
2237/0822	. . . Multiple sources	2237/201	. . for mounting multiple objects
2237/0825 for producing different ions simultaneously	2237/202	. . Movement
2237/0827 for producing different ions sequentially	2237/20207	. . . Tilt
2237/083	. . Beam forming	2237/20214	. . . Rotation
2237/0835	. . . Variable cross-section or shape	2237/20221	. . . Translation
2237/10	. Lenses		
2237/103	. . characterised by lens type		
2237/1035	. . . Immersion lens		
2237/12	. . electrostatic		
2237/1202	. . . Associated circuits		

- 2237/20228 Mechanical X-Y scanning
- 2237/20235 Z movement or adjustment
- 2237/20242 Eucentric movement
- 2237/2025 Sensing velocity of translation or rotation
- 2237/20257 Magnetic coupling
- 2237/20264 Piezoelectric devices
- 2237/20271 Temperature responsive devices
- 2237/20278 Motorised movement
- 2237/20285 computer-controlled
- 2237/20292 Means for position and/or orientation registration
- 2237/204 Means for introducing and/or outputting objects
- 2237/206 Modifying objects while observing
- 2237/2062 Mechanical constraints
- 2237/2065 Temperature variations
- 2237/2067 Surface alteration
- 2237/208 Elements or methods for movement independent of sample stage for influencing or moving or contacting or transferring the sample or parts thereof, e.g. probe needles or transfer needles in FIB/SEM systems
- 2237/21 Focus adjustment
- 2237/213 during electron or ion beam welding or cutting
- 2237/216 Automatic focusing methods
- 2237/22 Treatment of data
- 2237/221 Image processing
- 2237/223 Fourier techniques
- 2237/225 Displaying image using synthesised colours
- 2237/226 Image reconstruction
- 2237/228 Charged particle holography
- 2237/244 Detection characterized by the detecting means
- 2237/24405 Faraday cages
- 2237/2441 Semiconductor detectors, e.g. diodes
- 2237/24415 X-ray
- 2237/2442 Energy-dispersive (Si-Li type) spectrometer
- 2237/24425 Wavelength-dispersive spectrometer
- 2237/2443 Scintillation detectors
- 2237/24435 Microchannel plates
- 2237/2444 Electron Multiplier
- 2237/24445 using avalanche in a gas
- 2237/2445 Photon detectors for X-rays, light, e.g. photomultipliers
- 2237/24455 Transmitted particle detectors
- 2237/2446 Position sensitive detectors
- 2237/24465 Sectored detectors, e.g. quadrants
- 2237/2447 Imaging plates
- 2237/24475 Scattered electron detectors
- 2237/2448 Secondary particle detectors
- 2237/24485 Energy spectrometers
- 2237/2449 Detector devices with moving charges in electric or magnetic fields
- 2237/24495 Signal processing, e.g. mixing of two or more signals
- 2237/245 Detection characterised by the variable being measured
- 2237/24507 Intensity, dose or other characteristics of particle beams or electromagnetic radiation
- 2237/24514 Beam diagnostics including control of the parameter or property diagnosed
([H01J 2237/30472 takes precedence](#))
- 2237/24521 Beam diameter
- 2237/24528 Direction of beam or parts thereof in view of the optical axis, e.g. beam angle, angular distribution, beam divergence, beam convergence or beam landing angle on sample or workpiece
- 2237/24535 Beam current
- 2237/24542 Beam profile
- 2237/2455 Polarisation (electromagnetic beams)
- 2237/24557 Spin polarisation (particles)
- 2237/24564 Measurements of electric or magnetic variables, e.g. voltage, current, frequency
- 2237/24571 Measurements of non-electric or non-magnetic variables
- 2237/24578 Spatial variables, e.g. position, distance
- 2237/24585 Other variables, e.g. energy, mass, velocity, time, temperature
- 2237/24592 Inspection and quality control of devices
- 2237/248 Components associated with the control of the tube
- 2237/2482 Optical means
- 2237/2485 Electric or electronic means
- 2237/2487 using digital signal processors
- 2237/25 Tubes for localised analysis using electron or ion beams
- 2237/2505 characterised by their application
- 2237/2511 Auger spectrometers
- 2237/2516 Secondary particles mass or energy spectrometry
- 2237/2522 of electrons (ESCA, XPS)
- 2237/2527 Ions [SIMS]
- 2237/2533 Neutrals [SNMS]
- 2237/2538 Low energy electron microscopy [LEEM]
- 2237/2544 Diffraction [LEED]
- 2237/255 Reflection diffraction [RHEED]
- 2237/2555 Microprobes, i.e. particle-induced X-ray spectrometry
- 2237/2561 electron
- 2237/2566 ion
- 2237/2572 proton
- 2237/2577 atomic
- 2237/2583 using tunnel effects, e.g. STM, AFM
- 2237/2588 Lorenz microscopy (magnetic field measurement)
- 2237/2594 Measuring electric fields or potentials
- 2237/26 Electron or ion microscopes
- 2237/2602 Details
- 2237/2605 operating at elevated pressures, e.g. atmosphere
- 2237/2608 with environmental specimen chamber
- 2237/2611 Stereoscopic measurements and/or imaging
- 2237/2614 Holography or phase contrast, phase related imaging in general, e.g. phase plates
- 2237/2617 Comparison or superposition of transmission images; Moiré
- 2237/262 Non-scanning techniques
- 2237/2623 Field-emission microscopes
- 2237/2626 Pulsed source
- 2237/28 Scanning microscopes
- 2237/2801 Details
- 2237/2802 Transmission microscopes
- 2237/2803 characterised by the imaging method
- 2237/2804 Scattered primary beam
- 2237/2805 Elastic scattering
- 2237/2806 Secondary charged particle

2237/2807	X-rays	2237/3171	patterned
2237/2808	Cathodoluminescence	2237/31711	using mask
2237/2809	. . .	characterised by the imaging problems involved	2237/31713	Focused ion beam
2237/281	Bottom of trenches or holes	2237/31732	. . .	Depositing thin layers on selected microareas
2237/2811	Large objects	2237/31733	using STM
2237/2812	. . .	Emission microscopes	2237/31735	. . .	Direct-write microstructures
2237/2813	. . .	characterised by the application	2237/31737	using ions
2237/2814	Measurement of surface topography	2237/31738	using STM
2237/2815	Depth profile	2237/3174	. . .	Etching microareas
2237/2816	Length	2237/31742	for repairing masks
2237/2817	Pattern inspection	2237/31744	introducing gas in vicinity of workpiece
2237/2818	. . .	Scanning tunnelling microscopes	2237/31745	for preparing specimen to be viewed in microscopes or analyzed in microanalysers
2237/282	. .	Determination of microscope properties	2237/31747	using STM
2237/2823	. . .	Resolution	2237/31749	. . .	Focused ion beam
2237/2826	. . .	Calibration	2237/3175	. . .	Lithography
2237/285	. .	Emission microscopes	2237/31752	using particular beams or near-field effects, e.g. STM-like techniques
2237/2852	. . .	Auto-emission (i.e. field-emission)	2237/31754	using electron beams
2237/2855	. . .	Photo-emission	2237/31755	using ion beams
2237/2857	. . .	Particle bombardment induced emission	2237/31757	hybrid, i.e. charged particles and light, X-rays, plasma
2237/30	. .	Electron or ion beam tubes for processing objects	2237/31759	using near-field effects, e.g. STM
2237/303	. .	Electron or ion optical systems	2237/31761	Patterning strategy
2237/304	. .	Controlling tubes	2237/31762	Computer and memory organisation
2237/30405	. . .	Details	2237/31764	Dividing into sub-patterns
2237/30411	using digital signal processors [DSP]	2237/31766	Continuous moving of wafer
2237/30416	Handling of data	2237/31767	Step and repeat
2237/30422	Data compression	2237/31769	Proximity effect correction
2237/30427	using neural networks or fuzzy logic	2237/31771	using multiple exposure
2237/30433	. . .	System calibration	2237/31772	Flood beam
2237/30438	Registration	2237/31774	Multi-beam
2237/30444	Calibration grids	2237/31776	Shaped beam
2237/3045	Deflection calibration	2237/31777	by projection
2237/30455	. . .	Correction during exposure	2237/31779	from patterned photocathode
2237/30461	pre-calculated	2237/31781	from patterned cold cathode
2237/30466	. . .	Detecting endpoint of process	2237/31783	M-I-M cathode
2237/30472	. . .	Controlling the beam	2237/31784	Semiconductor cathode
2237/30477	Beam diameter	2237/31786	Field-emitting cathode
2237/30483	Scanning	2237/31788	through mask
2237/30488	Raster scan	2237/31789	Reflection mask
2237/30494	Vector scan	2237/31791	Scattering mask
2237/31	. .	Processing objects on a macro-scale	2237/31793	Problems associated with lithography
2237/3104	. . .	Welding	2237/31794	affecting masks
2237/3109	. . .	Cutting	2237/31796	affecting resists
2237/3114	. . .	Machining	2237/31798	detecting pattern defects
2237/3118	. . .	Drilling	2237/32	. .	Processing objects by plasma generation
2237/3123	. . .	Casting	2237/327	. .	Arrangements for generating the plasma
2237/3128	. . .	Melting	2237/33	. .	characterised by the type of processing
2237/3132	. . .	Evaporating	2237/332	. . .	Coating
2237/3137	Plasma-assisted co-operation	2237/3321	CVD [Chemical Vapor Deposition]
2237/3142	. . .	Ion plating	2237/3322	Problems associated with coating
2237/3146	Ion beam bombardment sputtering	2237/3323	uniformity
2237/3151	. . .	Etching	2237/3325	large area
2237/3156	. . .	Curing	2237/3326	high speed
2237/316	. . .	Changing physical properties	2237/3327	Coating high aspect ratio workpieces
2237/3165	. . .	Changing chemical properties	2237/3328	adhesion, stress, lift-off of deposited films
2237/317	. .	Processing objects on a microscale	2237/334	. . .	Etching
2237/31701	. . .	Ion implantation	2237/3341	Reactive etching
2237/31703	Dosimetry	2237/3342	Resist stripping
2237/31705	Impurity or contaminant control	2237/3343	Problems associated with etching
2237/31706	characterised by the area treated			
2237/31708	unpatterned			

2237/3344	isotropy
2237/3345	anisotropy
2237/3346	Selectivity
2237/3347	bottom of holes or trenches
2237/3348	control of ion bombardment energy
2237/335	. . .	Cleaning
2237/3355	Holes or apertures, i.e. inprinted circuit boards
2237/336	. . .	Changing physical properties of treated surfaces
2237/3365	Plasma source implantation
2237/338	. . .	Changing chemical properties of treated surfaces
2237/3382	Polymerising
2237/3385	Carburising
2237/3387	Nitriding
2237/339	. . .	Synthesising components

Details

2261/00	Gas- or vapour-discharge lamps
2261/02	. Details
2261/38	. . Devices for influencing the colour or wavelength of the light
2261/385	. . . Non-chemical aspects of luminescent layers, e.g. thickness profile, shape and distribution of luminescent coatings
2329/00	Electron emission display panels, e.g. field emission display panels
2329/002	. Cooling means
2329/005	. Multi-directional displaying, i.e. with multiple display faces facing in different directions
2329/007	. Vacuumless display panels, i.e. with phosphor directly applied to emitter without intermediate vacuum space
2329/02	. Electrodes other than control electrodes
2329/04	. . Cathode electrodes
2329/0402	. . . Thermionic cathodes
2329/0405	. . . Cold cathodes other than those covered by H01J 2329/0407 - H01J 2329/0492
2329/0407	. . . Field emission cathodes
2329/041 characterised by the emitter shape
2329/0413 Microengineered point emitters
2329/0415 conical shaped, e.g. Spindt type
2329/0418 needle shaped
2329/0421 Pillar shaped emitters
2329/0423 Microengineered edge emitters
2329/0426 Coatings on the emitter surface, e.g. with low work function materials
2329/0428 Fibres
2329/0431 Nanotubes
2329/0434 Particles
2329/0436 Whiskers
2329/0439 characterised by the emitter material
2329/0442 Metals or metal alloys
2329/0444 Carbon types
2329/0447 Diamond
2329/0449 Graphite
2329/0452 Fullerenes
2329/0455 Carbon nanotubes (CNTs)
2329/0457 Amorphous carbon
2329/046 Diamond-like carbon [DLC]

2329/0463	Semiconductor materials
2329/0465	Carbides
2329/0468	Nitrides
2329/0471	Borides
2329/0473	Oxides
2329/0476	. . .	Ferroelectric cathodes
2329/0478	. . .	Semiconductor cathodes, e.g. having PN junction layers
2329/0481	. . .	Cold cathodes having an electric field perpendicular to the surface thereof (H01J 2329/0407 - H01J 2329/0478 take precedence)
2329/0484	Metal-Insulator-Metal [MIM] emission type cathodes
2329/0486	. . .	Cold cathodes having an electric field parallel to the surface thereof, e.g. thin film cathodes
2329/0489	Surface conduction emission type cathodes
2329/0492	. . .	Cold cathodes combined with other synergetic effects, e.g. secondary, photo- or thermal emission
2329/0494	. . .	Circuit elements associated with the emitters by direct integration
2329/0497	Resistive members, e.g. resistive layers
2329/08	. .	Anode electrodes
2329/18	. .	Luminescent screens
2329/20	. .	characterised by the luminescent material
2329/22	. .	characterised by the binder or adhesive for securing the luminescent material to its support, e.g. substrate
2329/28	. .	with protective, conductive or reflective layers
2329/30	. .	Shape or geometrical arrangement of the luminescent material
2329/32	. .	Means associated with discontinuous arrangements of the luminescent material
2329/323	. . .	Black matrix
2329/326	. . .	Color filters structurally combined with the luminescent material
2329/46	. .	Arrangements of electrodes and associated parts for generating or controlling the electron beams
2329/4604	. .	Control electrodes
2329/4608	. . .	Gate electrodes
2329/4613	characterised by the form or structure
2329/4617	Shapes or dimensions of gate openings
2329/4621	Arrangement of gate openings
2329/4626	Curved or extending upwardly
2329/463	characterised by the material
2329/4634	Relative position to the emitters, cathodes or substrates
2329/4639	. . .	Focusing electrodes
2329/4643	characterised by the form or structure
2329/4647	Shapes or dimensions of focusing electrode openings
2329/4652	Arrangement of focusing electrode openings
2329/4656	characterised by the material
2329/466	Relative position to the gate electrodes, emitters, cathodes or substrates
2329/4665	In the same plane as the gate electrodes or cathodes
2329/4669	. . .	Insulation layers
2329/4673	. . .	for gate electrodes
2329/4678	. . .	for focusing electrodes
2329/4682	. . .	characterised by the shape

2329/4686 Dimensions of openings	2893/0013	. . . Sealed electrodes
2329/4691	. . . characterised by the material	2893/0015	. . . Non-sealed electrodes
2329/4695	. . Potentials applied to the electrodes	2893/0016 Planar grids
2329/86	. Vessels	2893/0017 Cylindrical, helical or annular grids
2329/8605	. . Front or back plates	2893/0018 Bar or cage-like grids
2329/861	. . . characterised by the shape	2893/0019	. . . Chemical composition and manufacture
2329/8615	. . . characterised by the material	2893/002 chemical
2329/862	. . Frames	2893/0021 carbon
2329/8625	. . Spacing members	2893/0022 Manufacture
2329/863	. . . characterised by the form or structure	2893/0023 carbonising and other surface treatments
2329/8635 having a corrugated lateral surface	2893/0024 Planar grids
2329/864	. . . characterised by the material	2893/0025 by winding wire upon a support
2329/8645	. . . with coatings on the lateral surfaces thereof	2893/0026	. . . Machines for manufacture of grids or anodes
2329/865	. . . Connection of the spacing members to the substrates or electrodes	2893/0027	. . . Mitigation of temperature effects
2329/8655 Conductive or resistive layers	2893/0029	. Electron beam tubes
2329/866 Adhesives	2893/003	. Tubes with plural electrode systems
2329/8665	. . . Spacer holding means	2893/0031	. Tubes with material luminescing under electron bombardment
2329/867	. . Seals between parts of vessels	2893/0032	. Tubes with variable amplification factor
2329/8675	. . . Seals between the frame and the front and/or back plate	2893/0033	. Vacuum connection techniques applicable to discharge tubes and lamps
2329/868	. . Passive shielding means of vessels	2893/0034	. . Lamp bases
2329/8685	. . . Antistatic shielding	2893/0035	. . . shaped as flat plates, in particular metallic
2329/869	. . . Electromagnetic shielding	2893/0036	. . . having wires, ribbons or tubes placed between two vessel walls and being perpendicular to at least one of said walls
2329/8695	. . . Mechanical shielding, e.g. against water or abrasion	2893/0037	. . Solid sealing members other than lamp bases
2329/88	. . Coatings on walls of the vessels (H01J 2329/18 , H01J 2329/868 , H01J 2329/89 take precedence)	2893/0038	. . . Direct connection between two insulating elements, in particular via glass material
2329/89	. . Optical components structurally combined with the vessel	2893/0039 Glass-to-glass connection, e.g. by soldering
2329/892	. . . Anti-reflection, anti-glare, viewing angle and contrast improving means	2893/004 Quartz-to-quartz connection
2329/895	. . . Spectral filters	2893/0041	. . . Direct connection between insulating and metal elements, in particular via glass material
2329/897	. . . Lenses	2893/0043 Glass-to-metal or quartz-to-metal, e.g. by soldering
2329/90	. Leading-in arrangements; seals therefor	2893/0044	. . . Direct connection between two metal elements, in particular via material a connecting material
2329/92	. Means forming part of the display panel for the purpose of providing electrical connection to it	2893/0045	. . Non-solid connections, e.g. liquid or rubber
2329/94	. Means for exhausting the vessel or maintaining vacuum within the vessel	2893/0046	. . Lamp base with closure
2329/941	. . Means for exhausting the vessel	2893/0047	. . Closure other than lamp base
2329/943	. . Means for maintaining vacuum within the vessel	2893/0048	. Tubes with a main cathode
2329/945	. . . by gettering	2893/0049	. . Internal parts
2329/946 characterised by the position or form of the getter	2893/005	. . Cathodes
2329/948 characterised by the material of the getter	2893/0051	. . Anode assemblies; screens for influencing the discharge
2329/96	. Circuit elements structurally associated with the display panels (H01J 2329/0494 takes precedence)	2893/0052	. . . Anode supporting means
2893/00	Discharge tubes and lamps	2893/0053	. . . Leading in for anodes; Protecting means for anode supports
2893/0001	. Electrodes and electrode systems suitable for discharge tubes or lamps	2893/0054	. . . Cooling means
2893/0002	. . Construction arrangements of electrode systems	2893/0055	. . Movable screens
2893/0003	. . . Anodes forming part of vessel walls	2893/0056	. . Parts inside tubes brought to incandescence by the discharge
2893/0004 Anodes formed in central part	2893/0058	. . Grids; Auxiliary internal or external electrodes
2893/0005	. . . Fixing of electrodes	2893/0059	. Arc discharge tubes
2893/0006 Mounting	2893/006	. Tubes with electron bombarded gas (e.g. with plasma filter)
2893/0007 Machines for assembly	2893/0061	. Tubes with discharge used as electron source
2893/0008 Supply leads; Electrode supports via rigid connection to vessel	2893/0062	. Tubes with temperature ionized gas as electron source
2893/0009 Electrode system pressing against vessel wall	2893/0063	. Plasma light sources
2893/001	. . Non-constructive schematic arrangements	2893/0064	. Tubes with cold main electrodes (including cold cathodes)
2893/0011	. . Non-emitting electrodes		
2893/0012	. . Constructional arrangements		

- 2893/0065 . . Electrode systems
- 2893/0066 . . . Construction, material, support, protection and temperature regulation of electrodes; Electrode cups
- 2893/0067 . . . Electrode assembly without control electrodes, e.g. including a screen
- 2893/0068 . . . electrode assembly with control electrodes, e.g. including a screen
- 2893/0069 . Tubes for displaying characters
- 2893/007 . Sequential discharge tubes
- 2893/0072 . Disassembly or repair of discharge tubes
- 2893/0073 . . Discharge tubes with liquid poolcathodes; constructional details
- 2893/0074 . . . Cathodic cups; Screens; Reflectors; Filters; Windows; Protection against mercury deposition; Returning condensed electrode material to the cathodic cup; Liquid electrode level control
- 2893/0075 Cathodic cups
- 2893/0076 Liquid electrode materials
- 2893/0077 Cathodic cup construction; Cathodic spot control
- 2893/0078 Mounting cathodic cups in the discharge tube
- 2893/0079 Means for limiting the cathodic spot movement
- 2893/008 Means for stabilising the cathodic spot
- 2893/0081 Cooling means
- 2893/0082 Returning condensed electrode material to the cathodic cup, e.g. including cleaning
- 2893/0083 Liquid electrode level control
- 2893/0084 Protection against mercury deposition
- 2893/0086 Gas fill; Maintaining or maintaining desired pressure; Producing, introducing or replenishing gas or vapour during operation of the tube; Getters; Gas cleaning; Electrode cleaning
- 2893/0087 Igniting means; Cathode spot maintaining or extinguishing means
- 2893/0088 . . Tubes with at least a solid principal cathode and solid anodes
- 2893/0089 . . . Electrode systems
- 2893/009 . . . Anode systems; Screens
- 2893/0091 Anode supporting means
- 2893/0092 Anodic screens or grids
- 2893/0093 Anodic arms
- 2893/0094 . . . Electrode arrangements; Auxiliary electrodes
- 2893/0095 . . Tubes with exclusively liquid main electrodes
- 2893/0096 . Transport of discharge tube components during manufacture, e.g. wires, coils, lamps, contacts, etc.
- 2893/0097 . . Incandescent wires of coils
- 2893/0098 . . Vessels